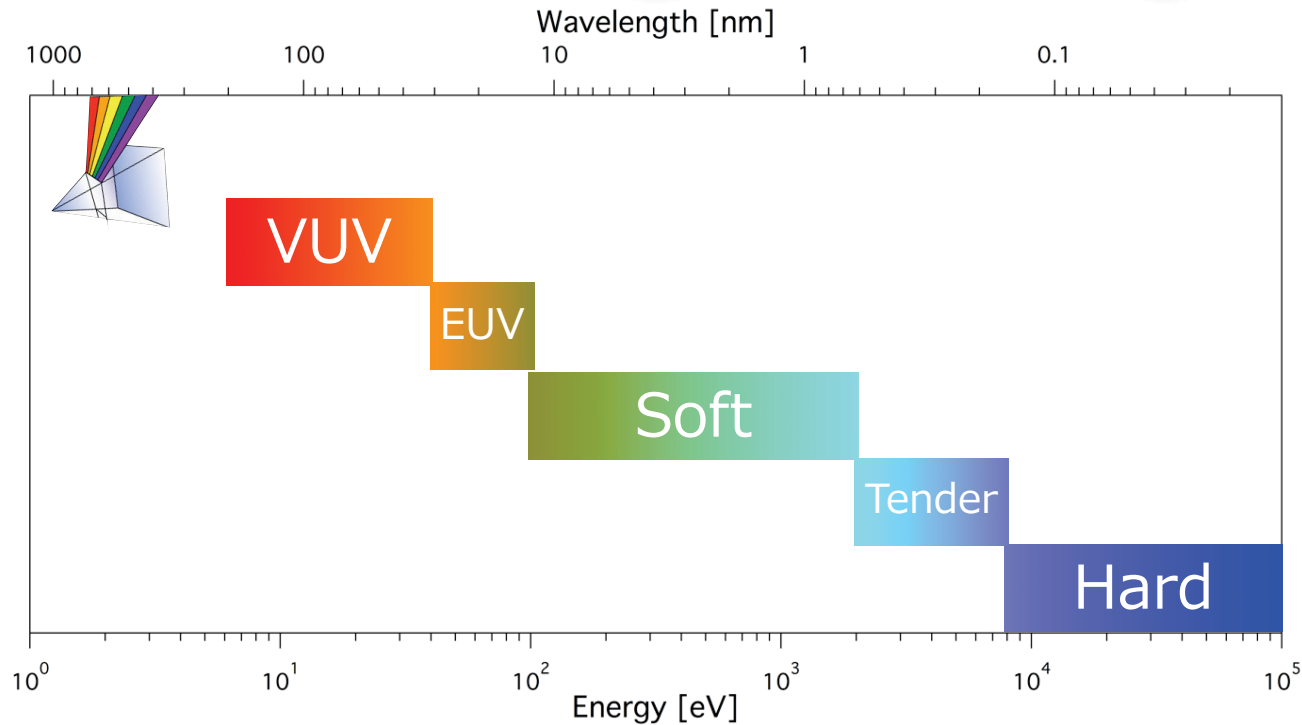


Pixels for Soft X-ray Microscopies



Soft X-rays

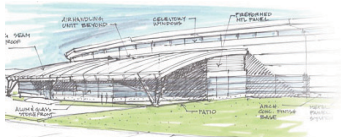
- Non-penetrating
- Chemistry
 - Where are the electrons?
 - What are they doing?

Hard X-rays

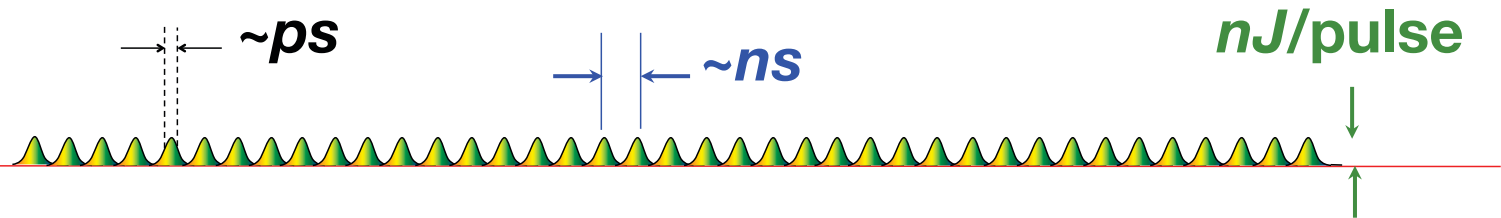
- Penetrating
- Structure
 - Where are the atoms?

Sources of (bright) X-rays

Storage Rings



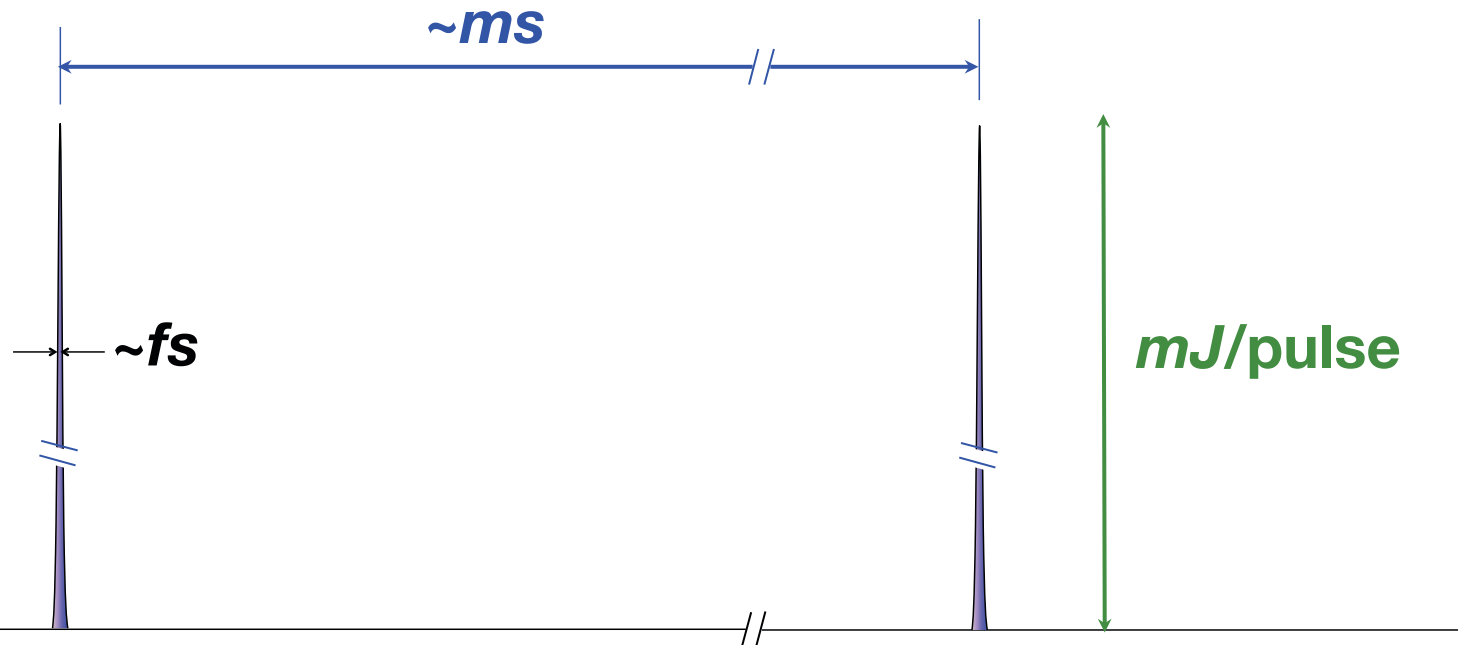
NSLS-II



FELs

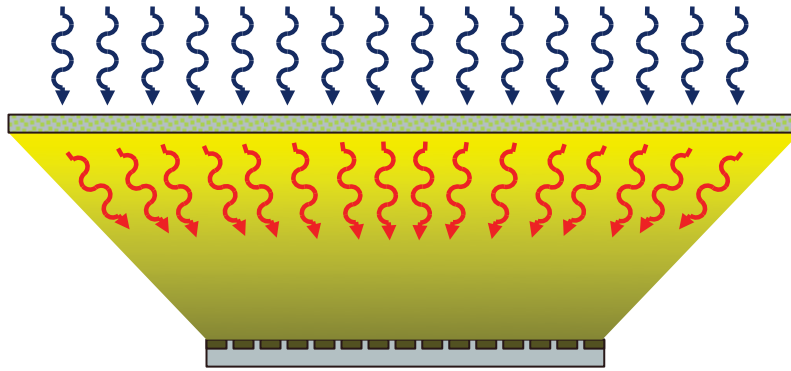


LCLS



comparable average power

Direct X-ray Detection



phosphor fiber-optically
coupled to CCD

This was (is) the ubiquitous
X-ray / electron detector

- easy to make large areas
- radiation resistant



Large impact of
Pilatus (PSI)

- Hybrid Pixel
- Leverage LHC
- typ. 12 keV X-ray \leftrightarrow $>3,000$ e $^-$
- Count individual X-rays
 - (not so simple, but ...)



Detector Requirements

 Geometric:

- 🌐 2D (pixilated) detector

-  N x N pixels

- Pitch \mathbf{p} $\delta \mathbf{x}$
Size

- Dimension **D** = $N \times p$

- Thickness $T(E_\gamma)_{MAX}$

 Electric:

- Frame rate $1/\Delta t$  

- 
- Noise*

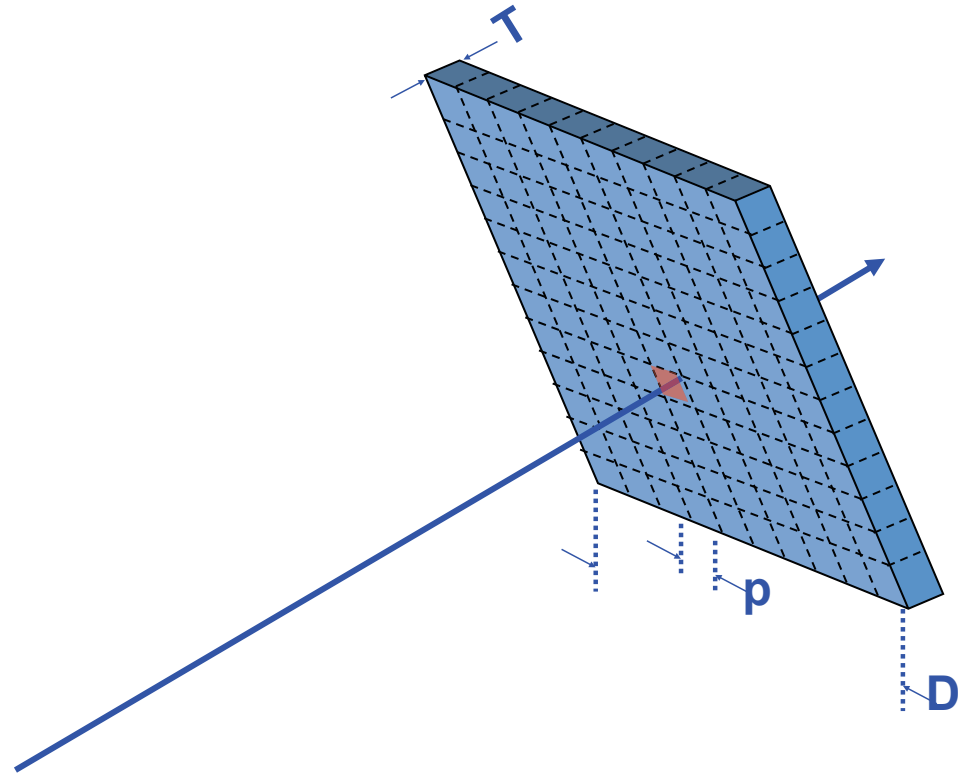
- Full-scale per pixel Q_{MAX} Q
Intensity

- SR: Counting detector $\mathbf{N}(\mathbf{x}, \mathbf{y})$

- SR: Single photon detector ($\mathbf{x}, \mathbf{y}, t$) - *better* ($\mathbf{x}, \mathbf{y}, E, t$)

- FEL: all photons arrive at the same time → integrating detector $Q(x,y)$

*Need gain for SXR counting pixel



Problem Statement

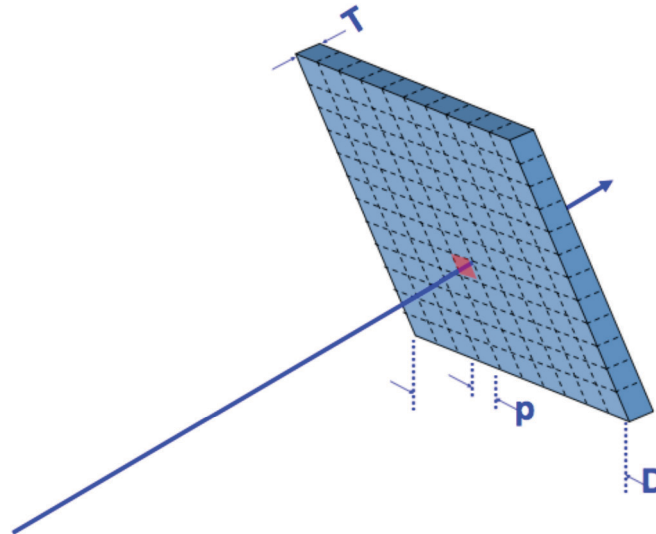
Meet these requirements

Detector Requirements

Geometric:

2D (pixilated) detector

- $N \times N$ pixels
- Pitch p
- Dimension $D = N \times p$
- Thickness $T(E_y)_{MAX}$



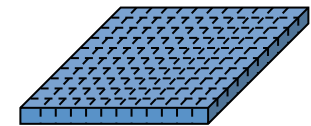
Electric:

- Frame rate $1/\Delta t$
- Noise
- Full-scale per pixel Q_{MAX}
- FEL: all photons arrive at the same time \rightarrow integrating detector

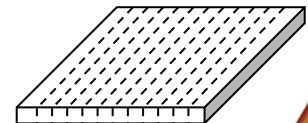
- and cheap
- and easy to use
- and developed quickly

Implementation

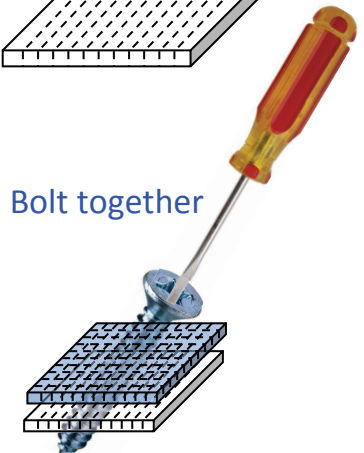
Identify suitable sensor



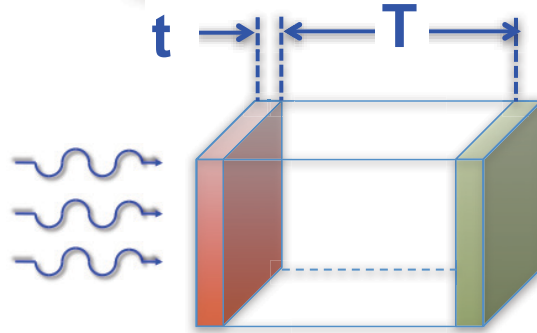
Design suitable readout and data acquisition



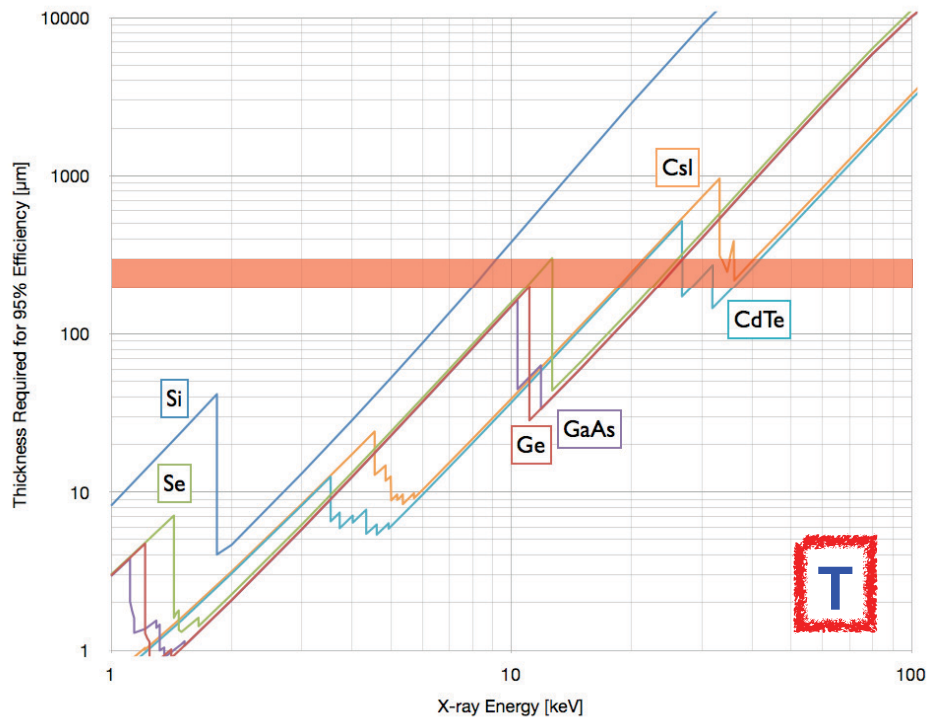
Bolt together



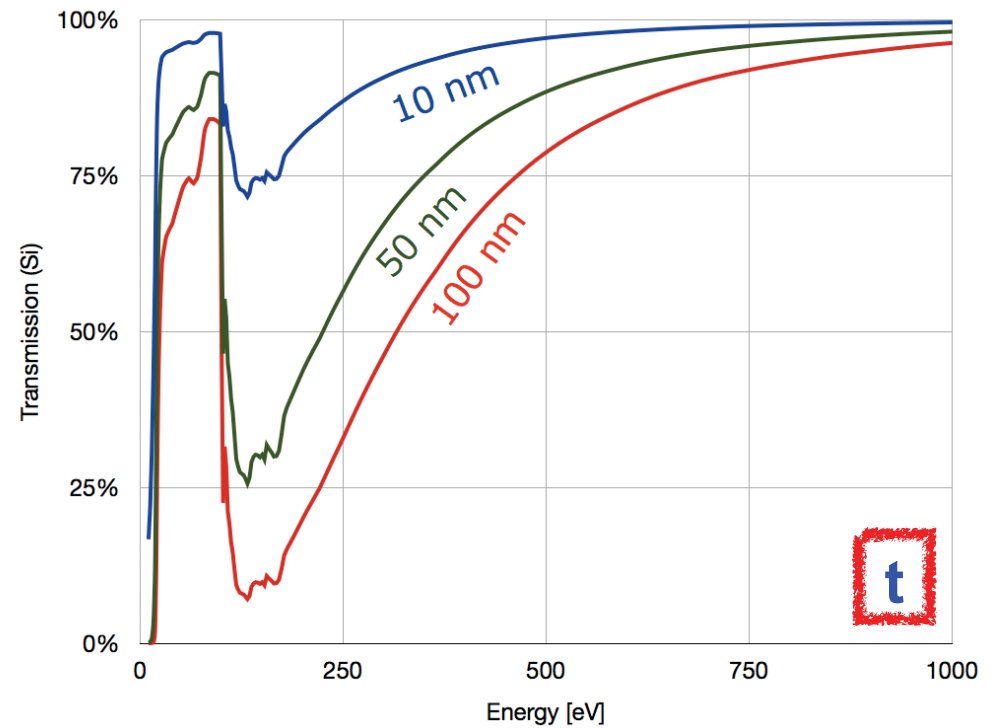
Sensor Challenges



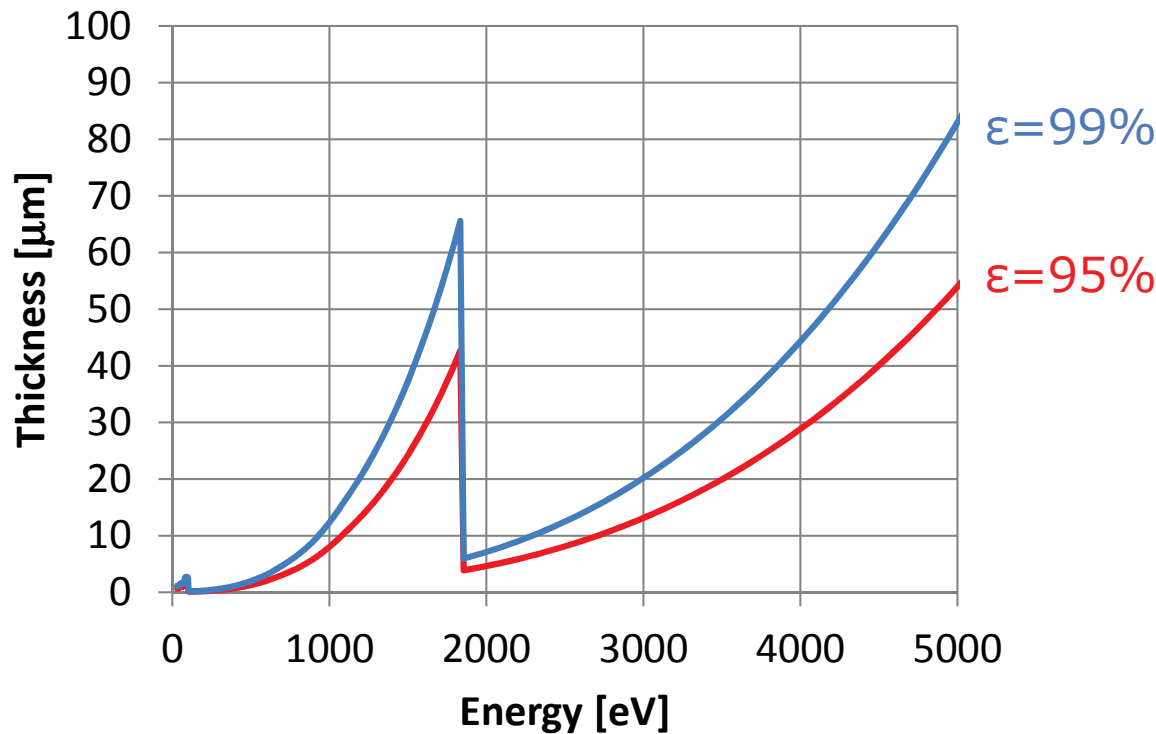
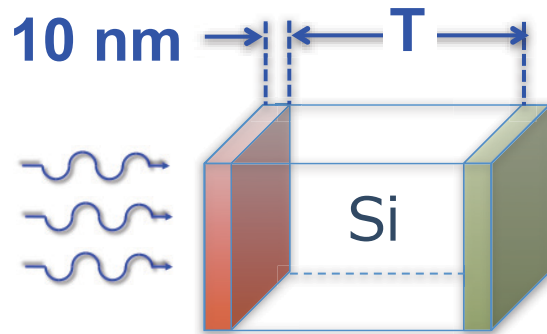
Hard X-rays



Soft X-rays

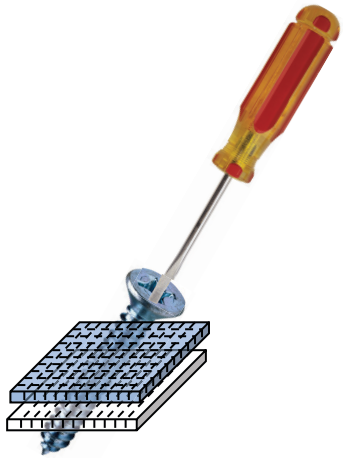


Ideal for Soft X-rays



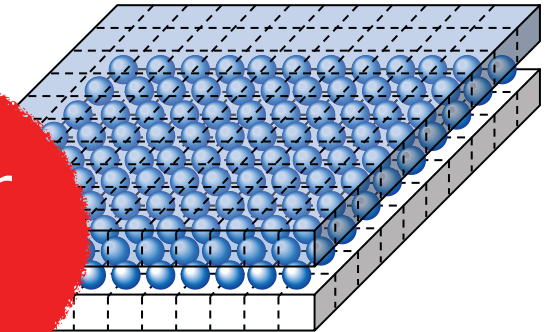
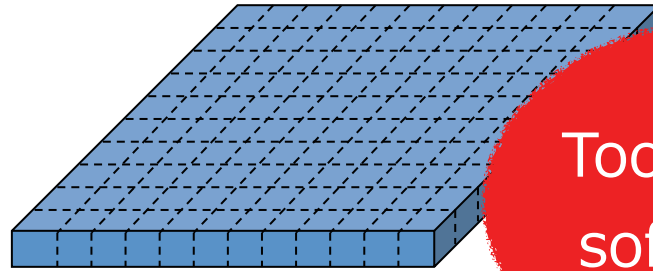
- Silicon
- 50 - 100 μm thick
- 10 nm contact
- High resistivity substrate
 - Full depletion
 - Minimize diffusion
 - Maximize spatial resolution
 - Maximize charge (energy) resolution

Interconnect



Monolithic

Hybrid

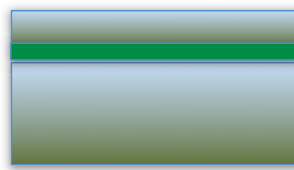


Too high for
soft X-rays

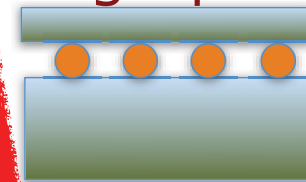
CCD on thick,
high-p Si



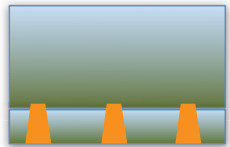
CMOS, SOI
on thick, high-p Si



Hybrid on thick,
high-p Si



3D

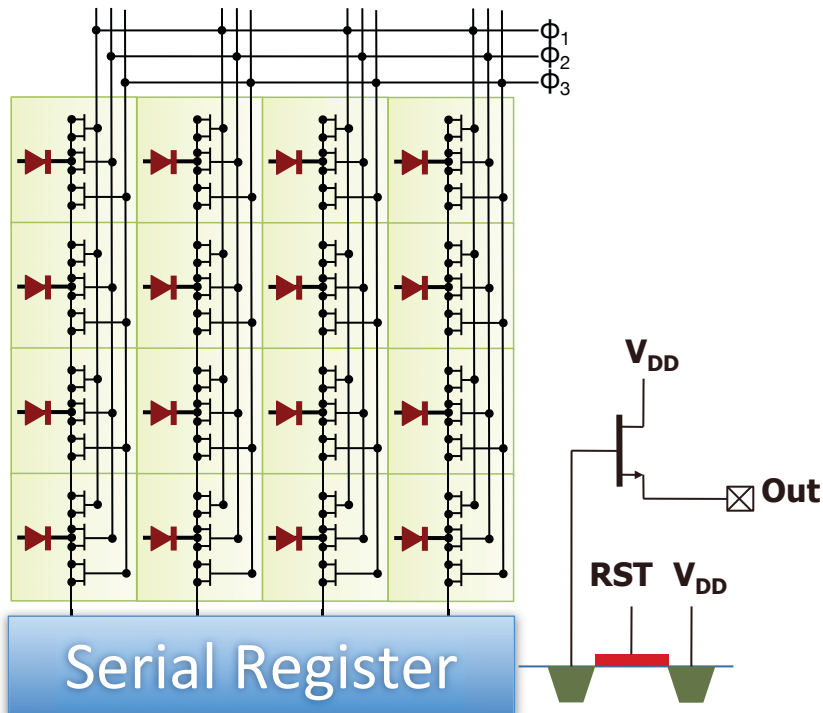


Pixel Size	$\leq 10 - < 50 \mu\text{m}$	$\leq 5 - < 20 \mu\text{m}$	$50 - 100 \mu\text{m}$	
Area	$10^2 - 10^3 \mu\text{m}^2$	$10^1 - 10^3 \mu\text{m}^2$	$10^3 - 10^4 \mu\text{m}^2$	
$\frac{H}{\text{pixel}}$	0	$10^0 - 10^2$	$10^2 - 10^3$	
ENC	$10^0 - 10^1 e^-$	$10^1 e^-$	$10^2 e^-$	

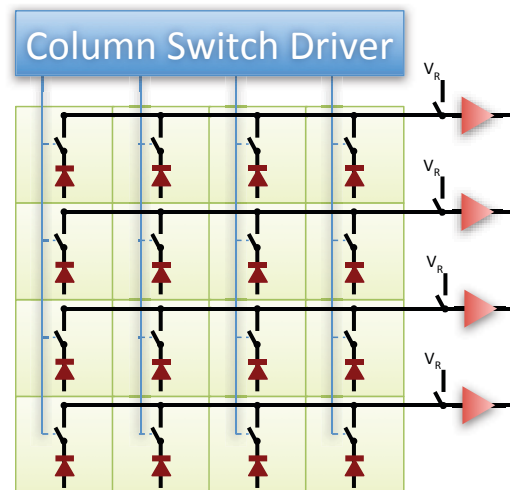
Different detailed mechanisms, but lower noise with monolithic pixels

Monolithic Approaches on thick, high-resistivity silicon

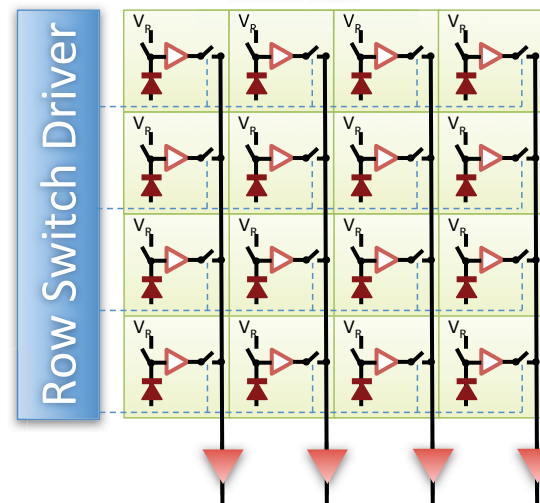
CCD



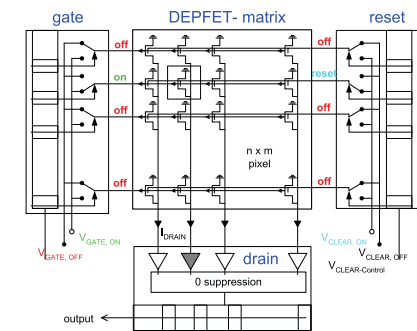
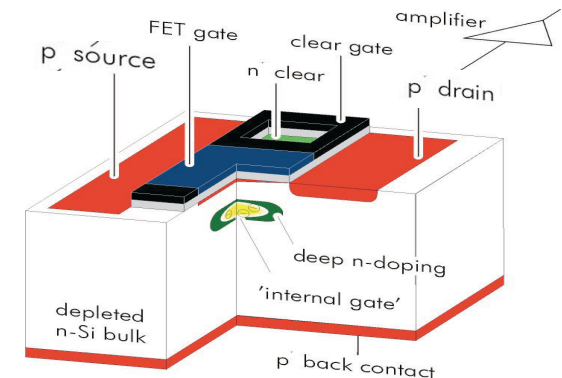
PPS



APS



DEPFET



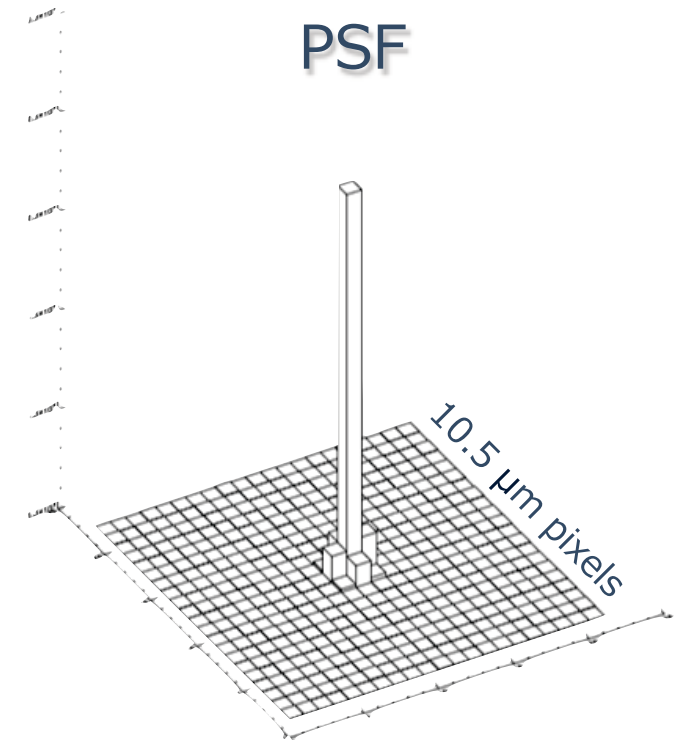
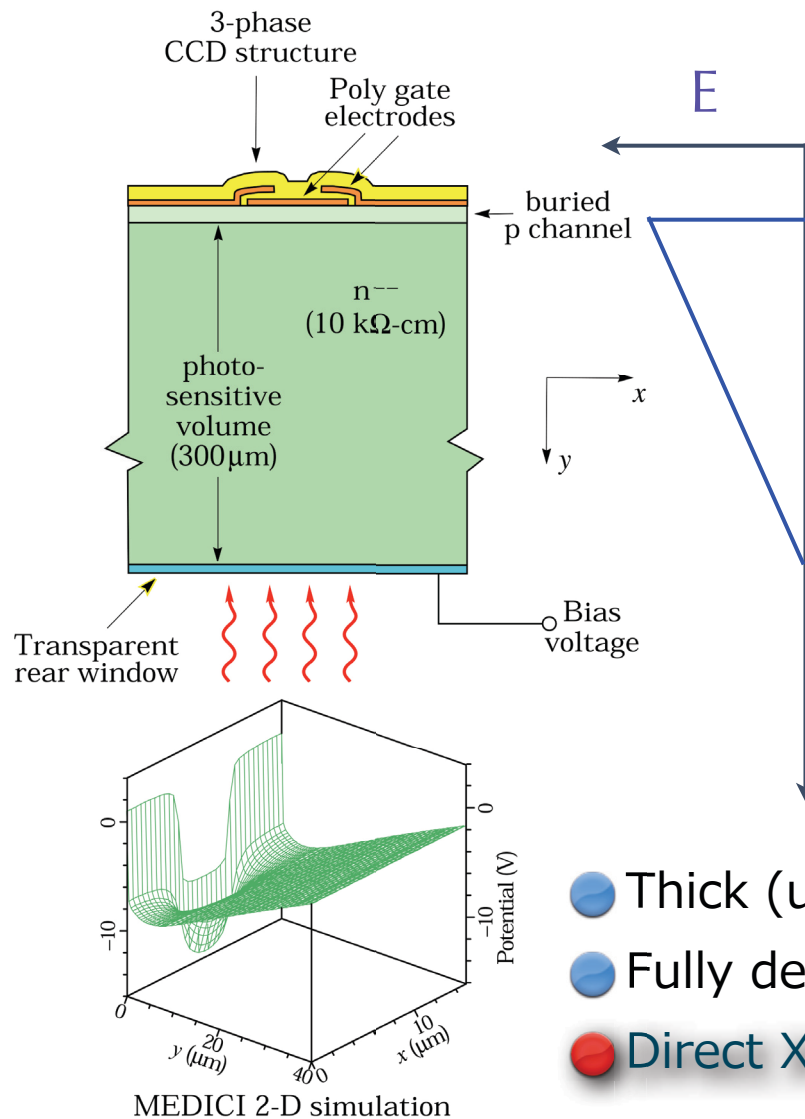
3D



Physics:
MMIX

CMOS (?)
SOI

LBNL CCD

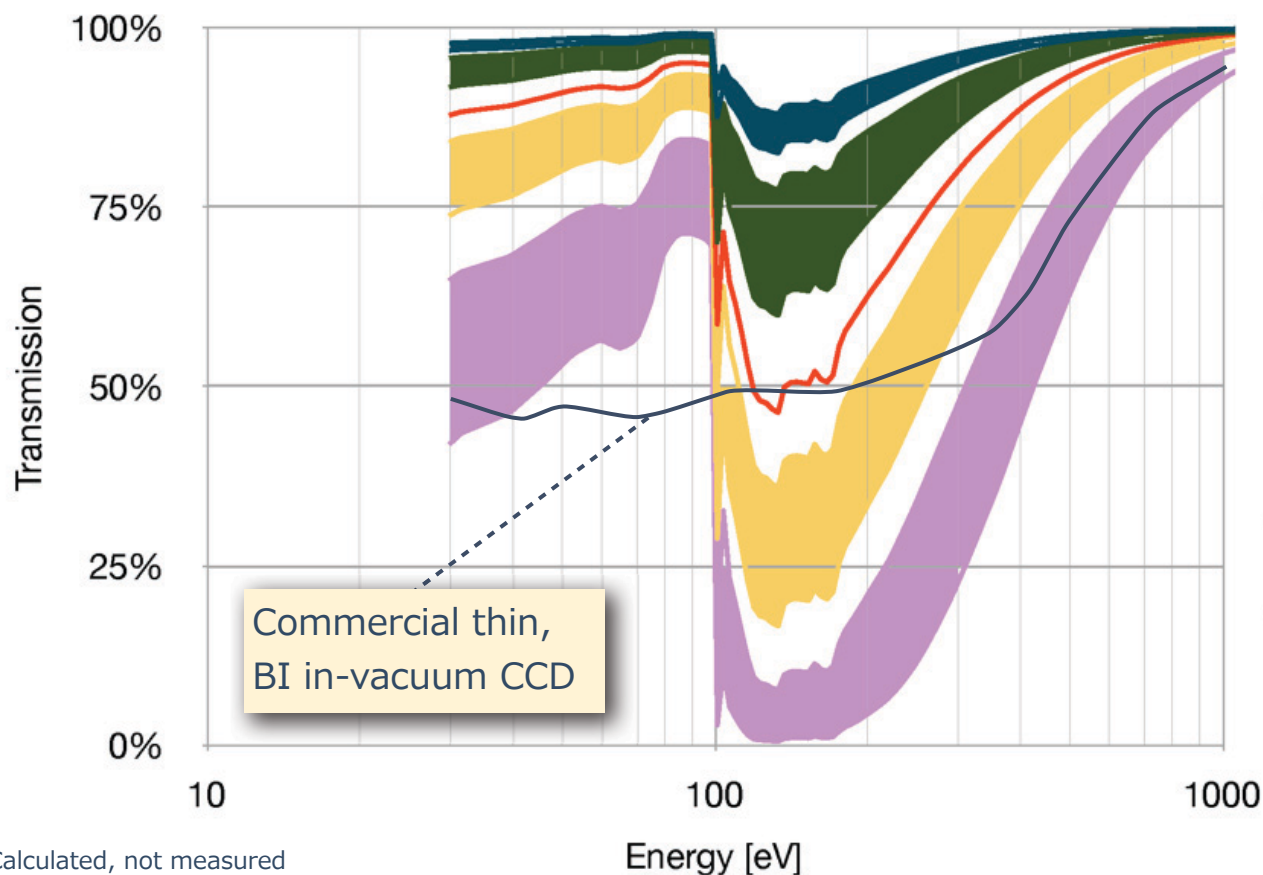


At $V_{\text{SUB}} = 115 \text{ V}$,
 $\sigma_D = 3.7 \pm 0.2 \text{ } \mu\text{m}$

- Thick (up to 650 μm) high-resistivity Si
- Fully depleted
- Direct X-ray detection
- n-type (p-channel) for enhanced radiation resistance

Thin Contact Development

Process	Window thickness	Status
Low energy implantation + 500 C annealing	1,000-2,000 Å	Standard process for 800 eV+ devices
Low energy implantation + laser annealing	400-700 Å	Works, but low yield
a-Si contact deposition by sputtering	300 Å	Works, but high leakage
In-situ doped poly (ISDP)	100-250 Å	Recent progress - 100 Å demonstrated
Molecular Beam Epitaxy	50-75 Å	R&D (MBE system being assembled now)



- Low temperature process desired
 - Apply after all other process steps complete
- robust, simple, fast
- ultimate performance
- R&D

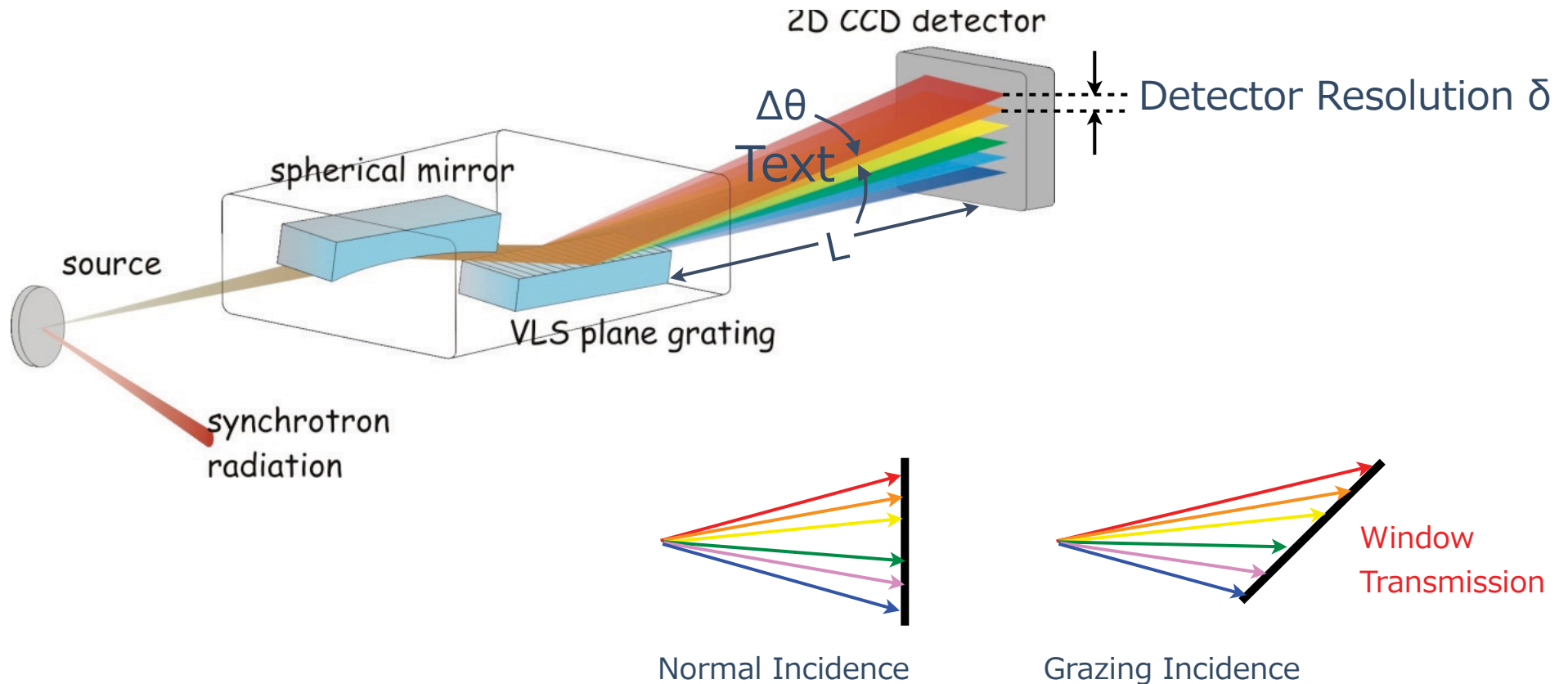
Calculated, not measured

Spectroscopy (with Grating)

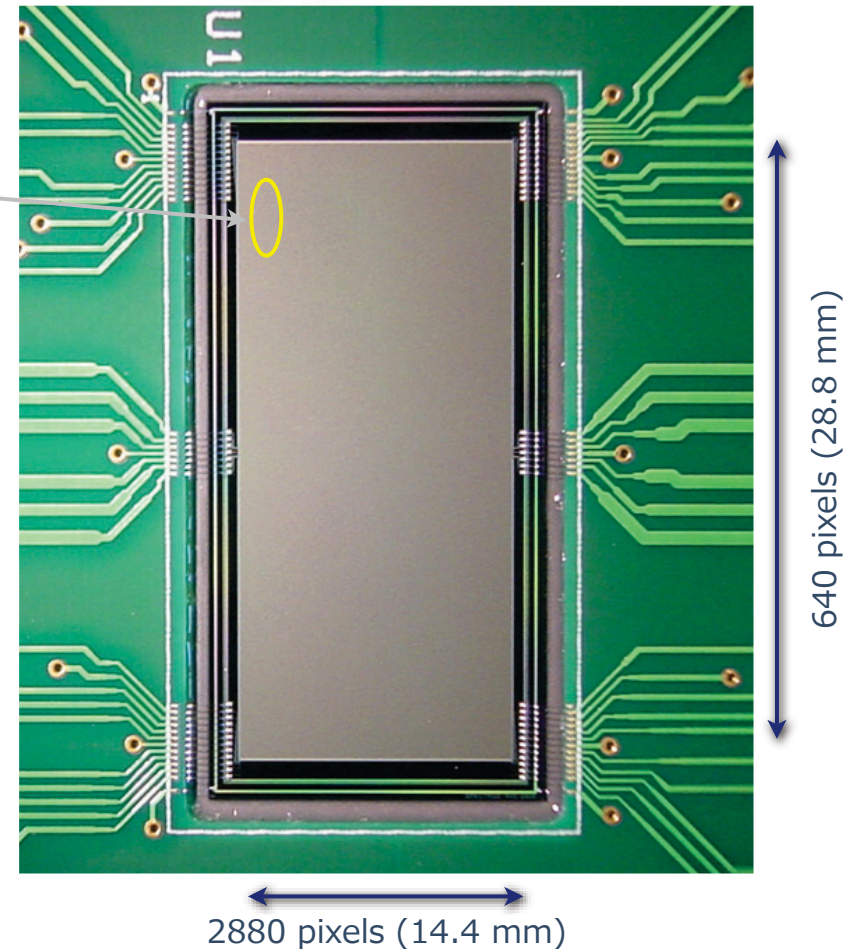
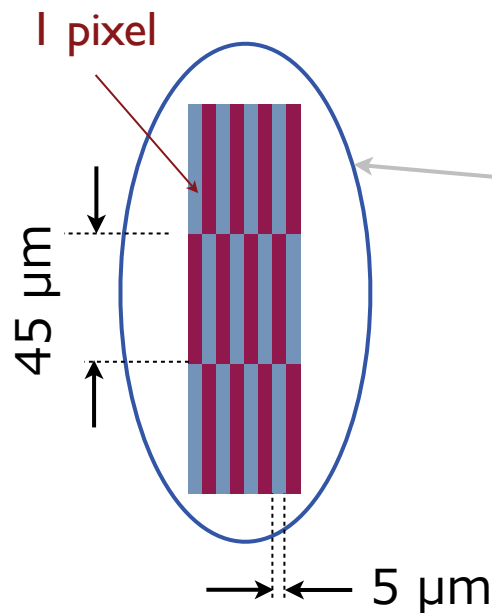


Example

- For a given resolution, $\Delta\theta = \delta/L$
- Smaller δ allows shorter beamline (L)
- Today $\delta \sim 15 \mu\text{m}$ (can always do better with single photons)



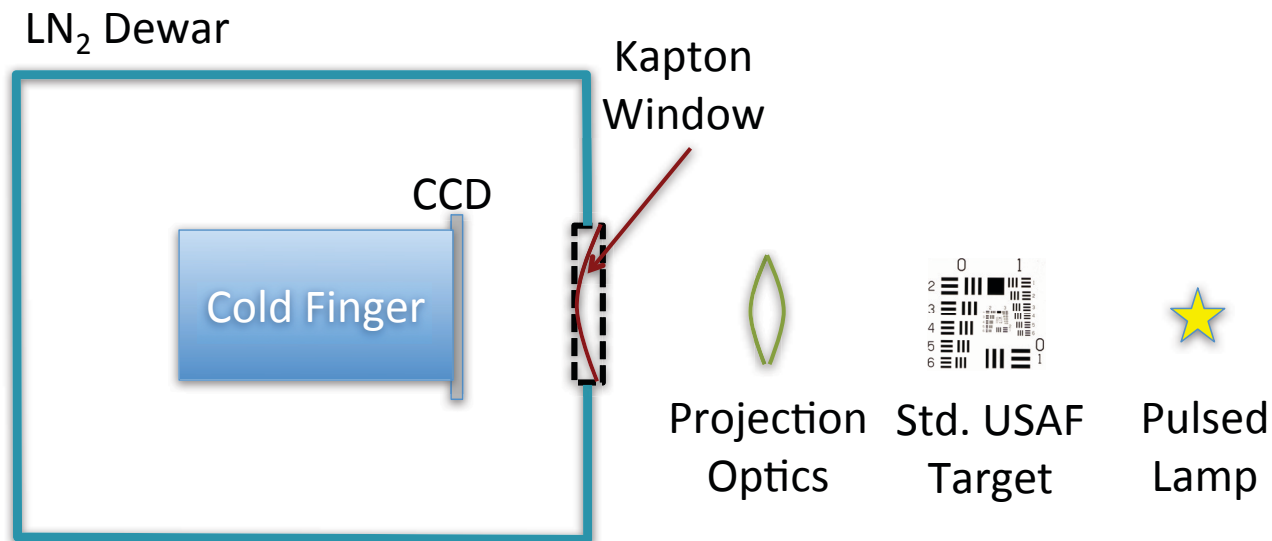
Fine-pitch CCD for Spectroscopy



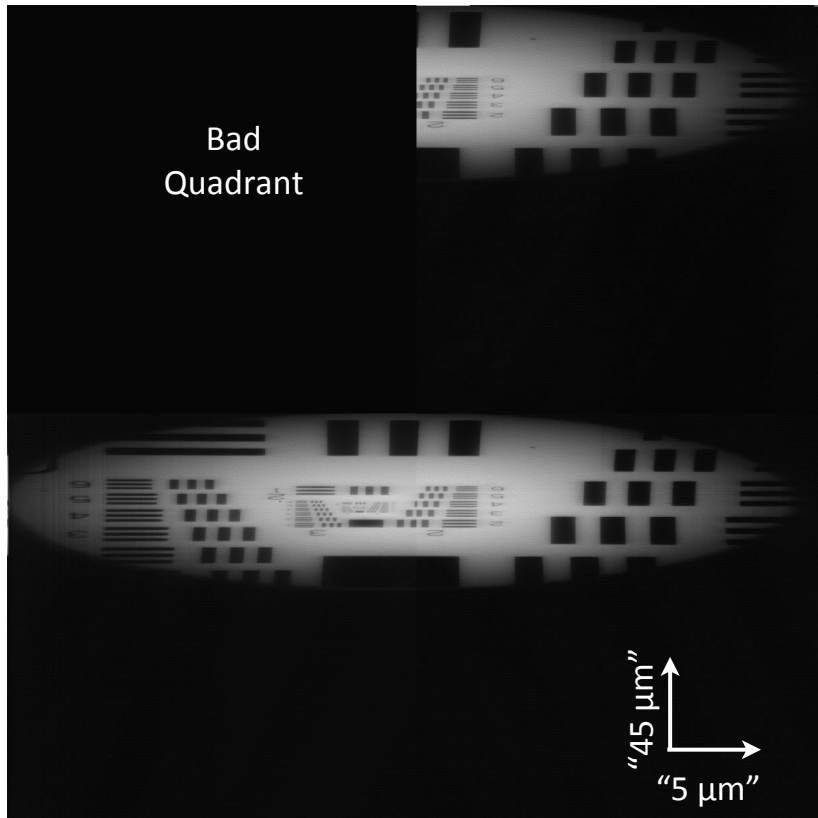
- "Conventional" 4-port CCD
 - $2880 \times 640 = 1.8 \times 10^6$ pixels
 - 4 ports $\rightarrow 4.6 \times 10^5$ pixels / port
 - ~ 5 (10) second readout at 100 (50) kHz
- "Interdigitated" gate structure

Optical Test

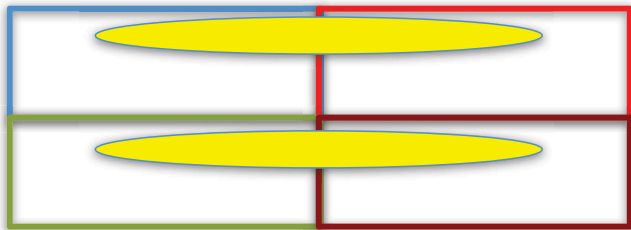
- 5 μm pitch necessitated unconventional gate structure
 - Does it work?
- First look – project USAF target (as best as possible) onto CCD



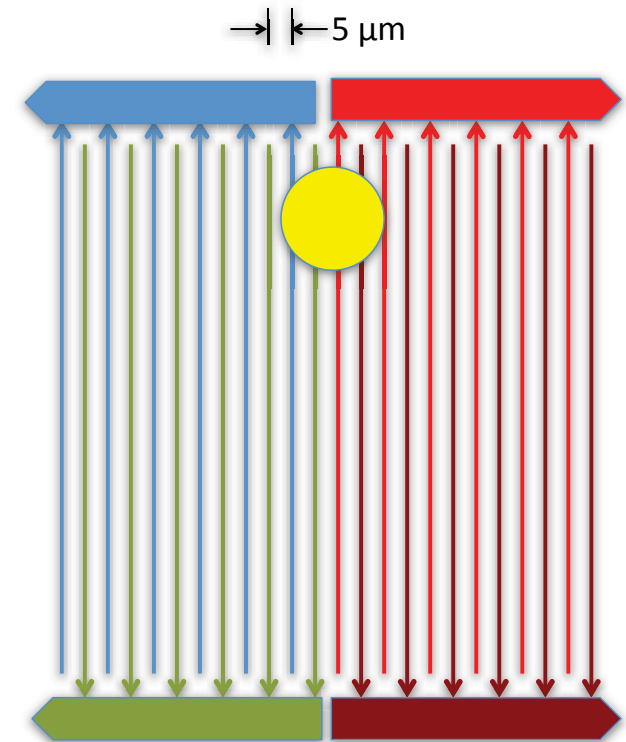
1st Light (03.13)



Mapping onto 4-port readout
(represented by square pixels)

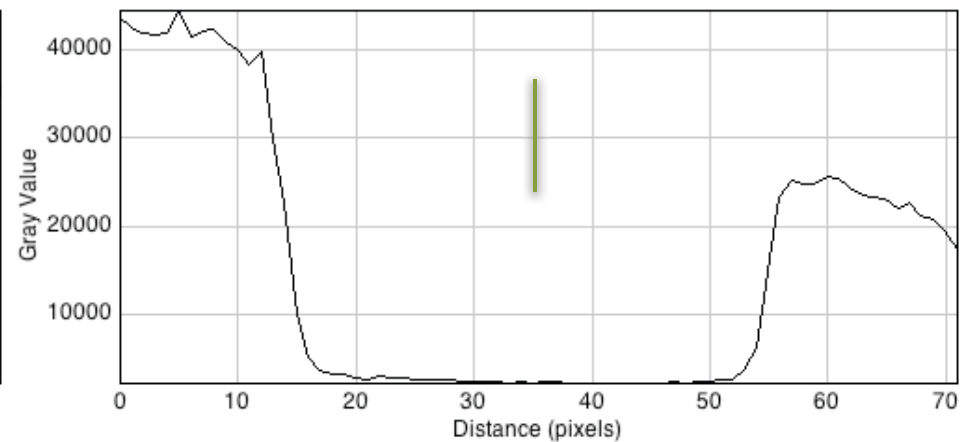
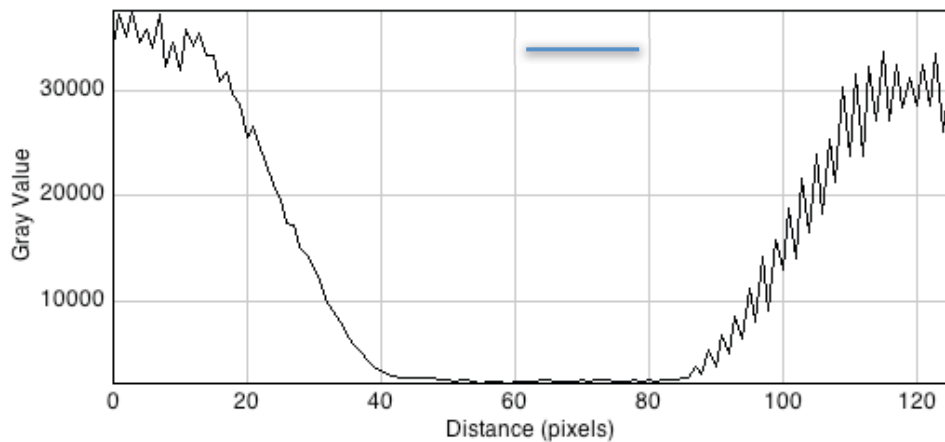
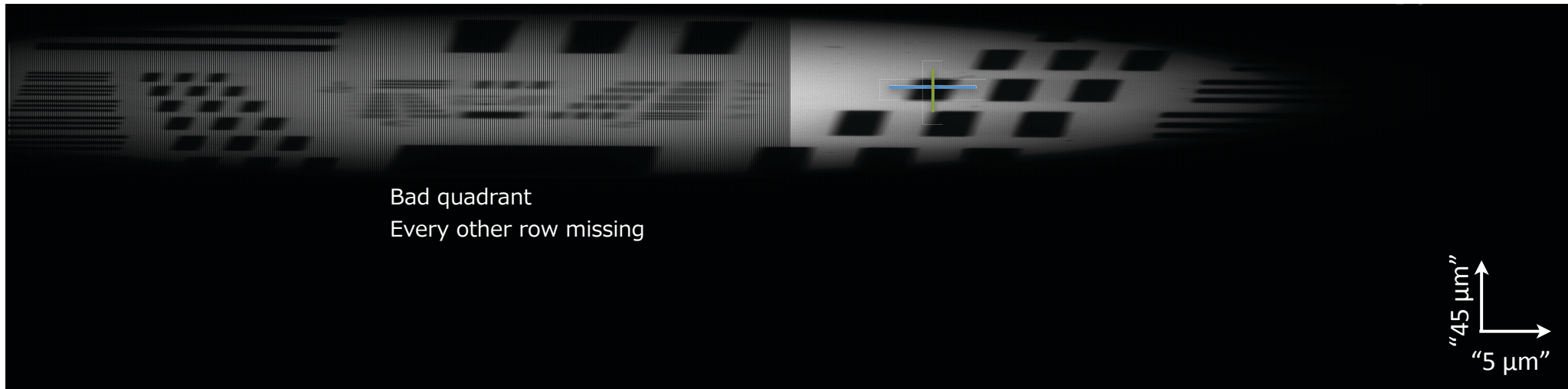


- USAF target
 - Hand-focused onto CCD
- Behavior correct
 - Validates that unorthodox clocking scheme works (the only real question)
- One bad quadrant (wire bond)



As Expected

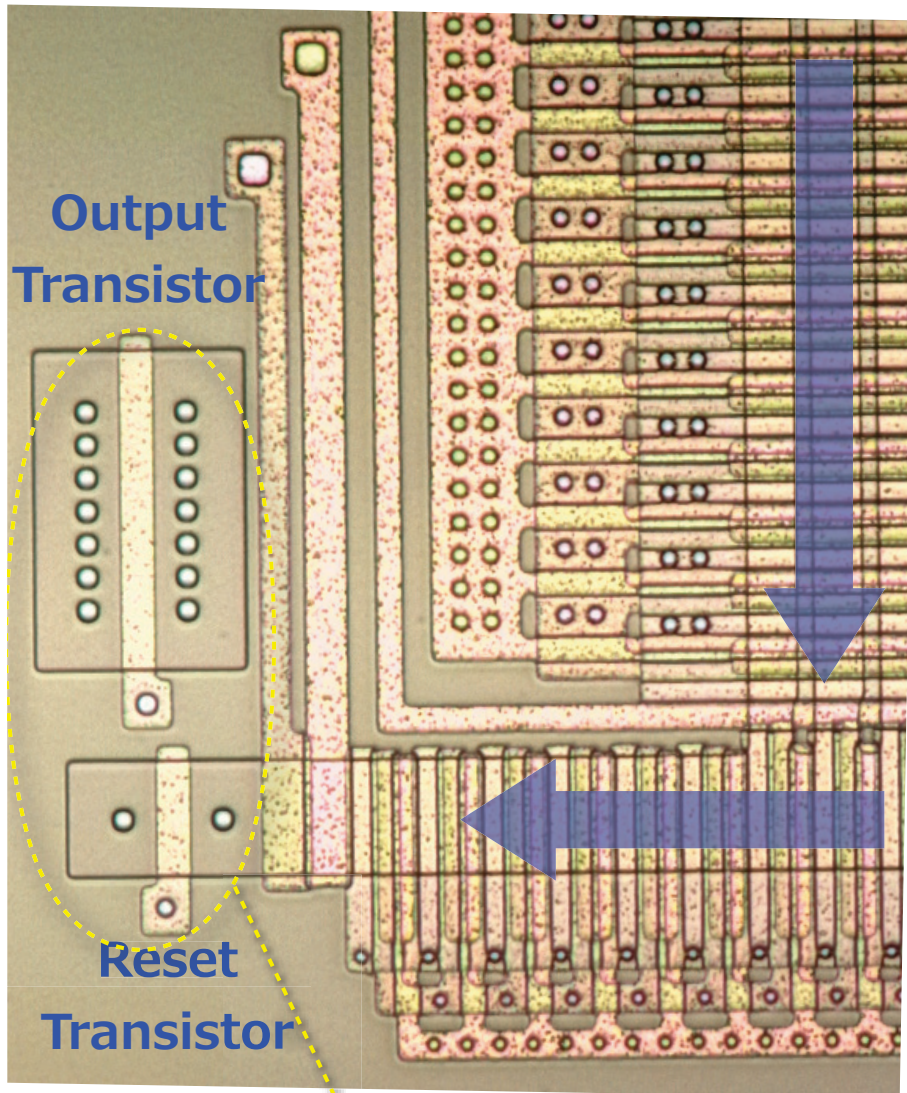
Descramble



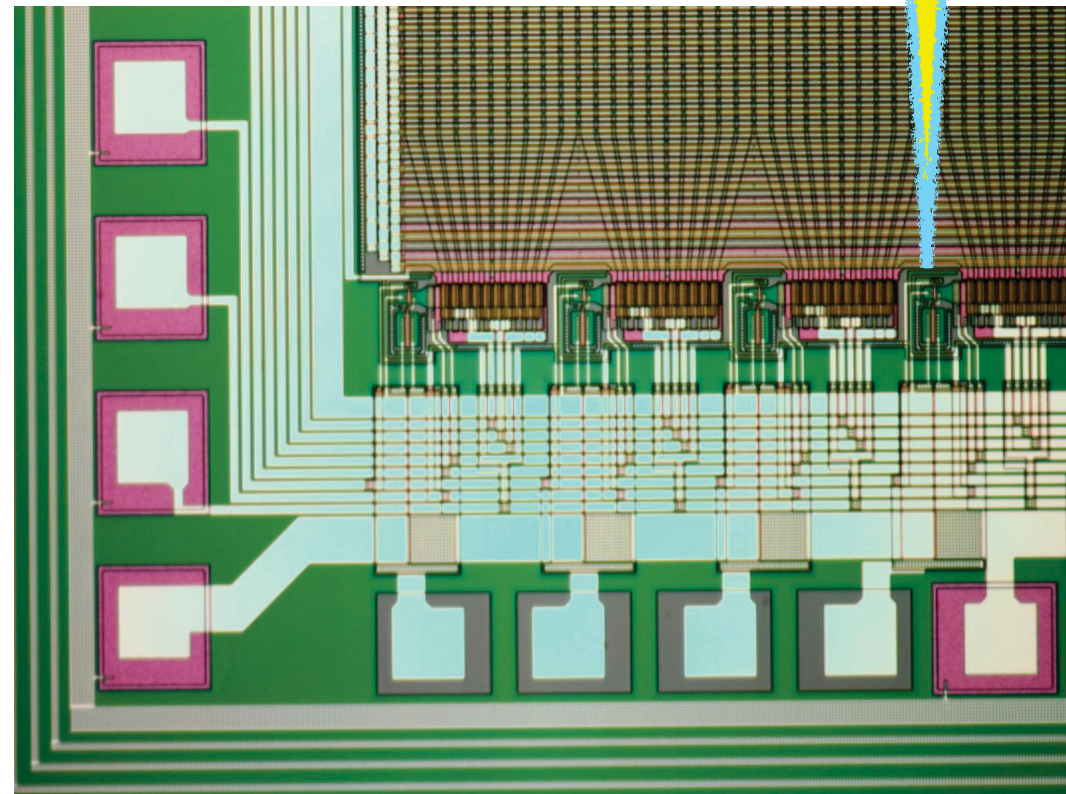
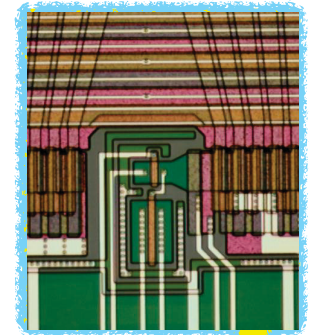
Next: characterize at ALS BL 5.3.1

(almost) Column-Parallel CCD

Conventional CCD

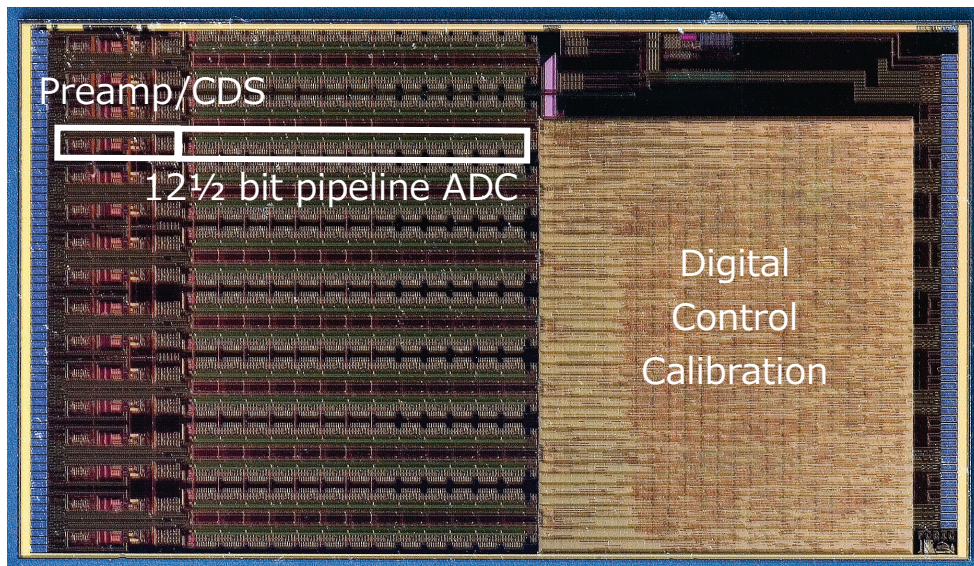
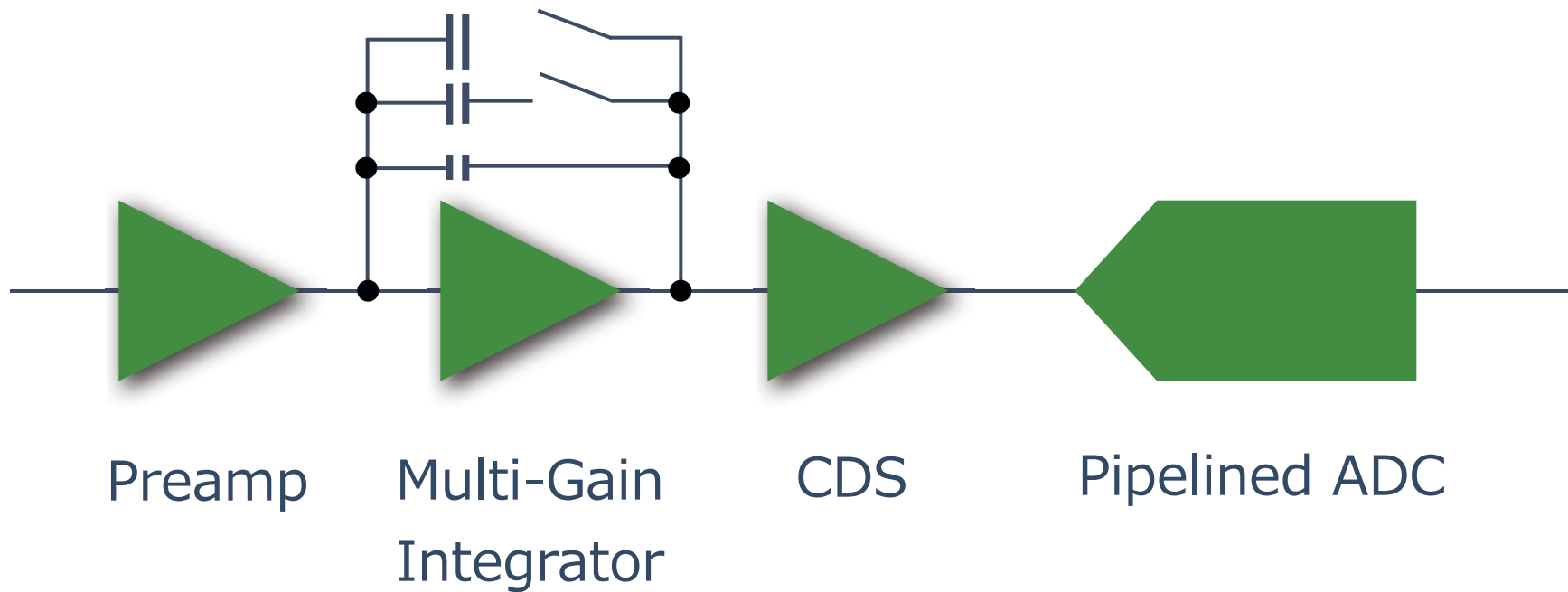


Speed up CCDs from $O(10^{-1})$ Hz to $O(10^2)$ Hz per megapixel



Where to put these transistors?

16-Channel Custom Readout IC



- Gain 8, 2, 1
- 12+1 bit ADC
- Covers 15 bit range
- 300 μm input pad pitch

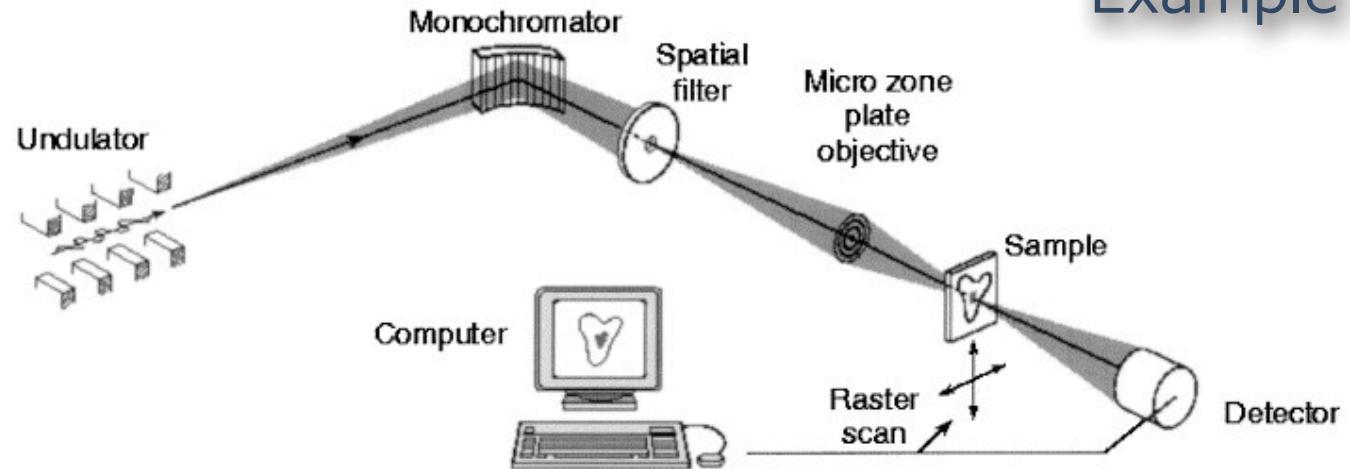
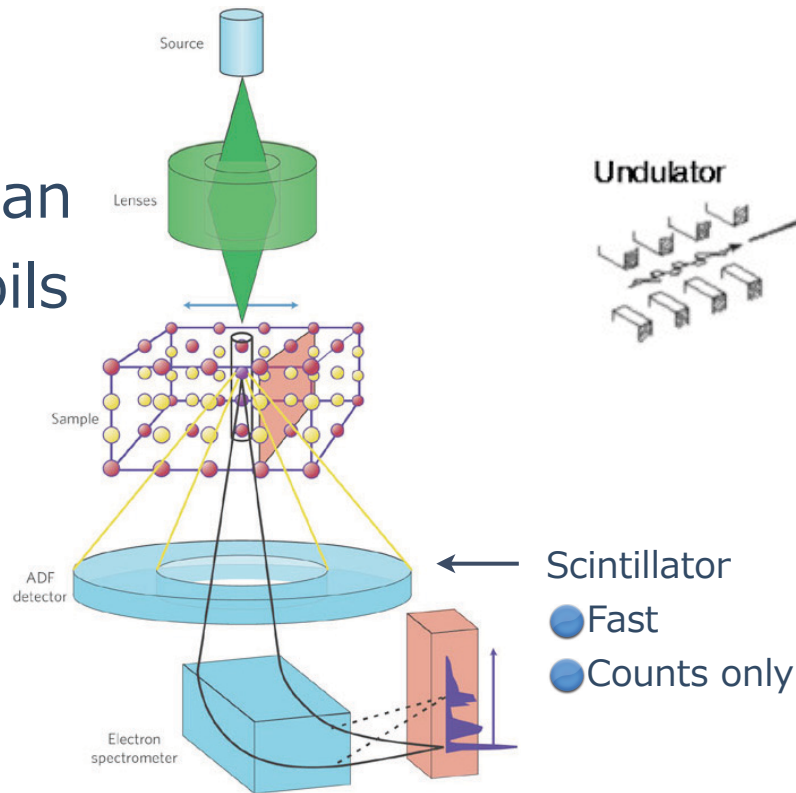
0.25 μm CMOS - 2006

Scanning Microscopies



Example

Scan
Coils



**Acquisition Times from
Minutes → Seconds**

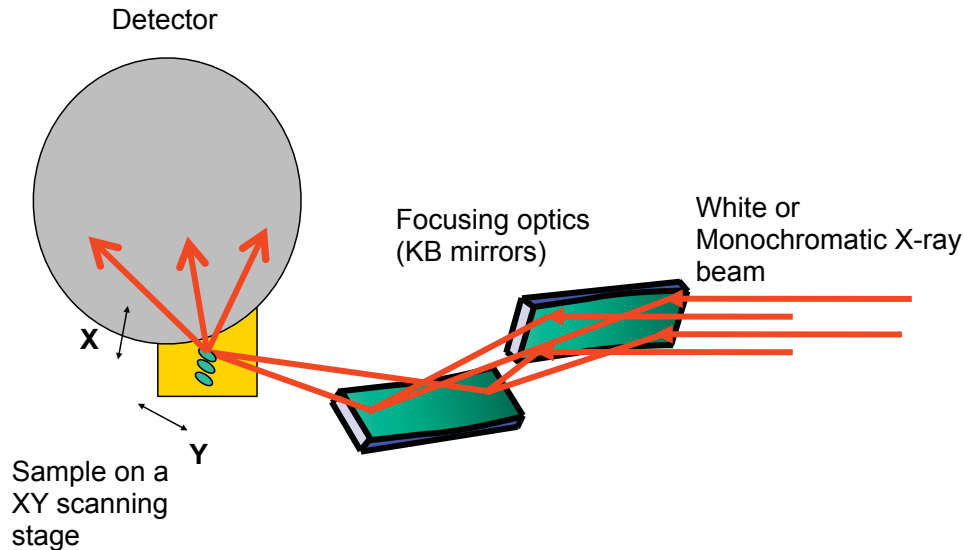
STEM

- Raster scan the electron beam
- Each “dwell” point is a pixel
- Datum is “scattered intensity”

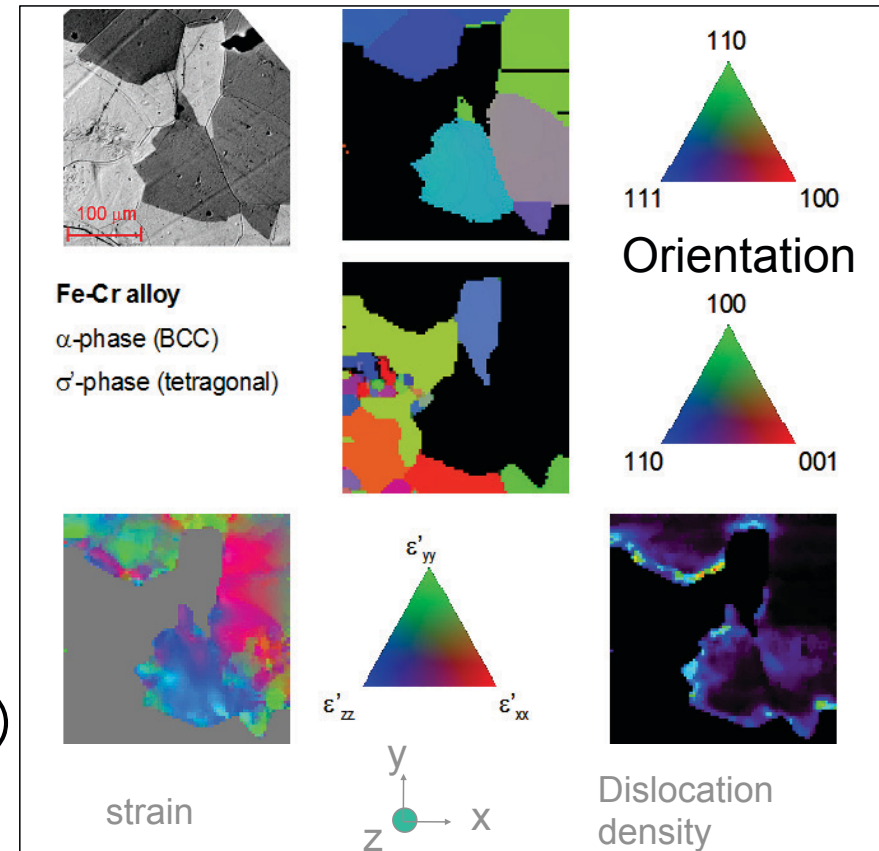
STXM

- Raster scan the sample
- Each “dwell” point is a pixel
- Datum is “scattered intensity”

Polychromatic Laue Microdiffraction



- Conv. CCD: ≥ 12 hr for a scan
- Scan monochromatic beam (N energies) and use a counting detector
- Fast energy-resolving detector

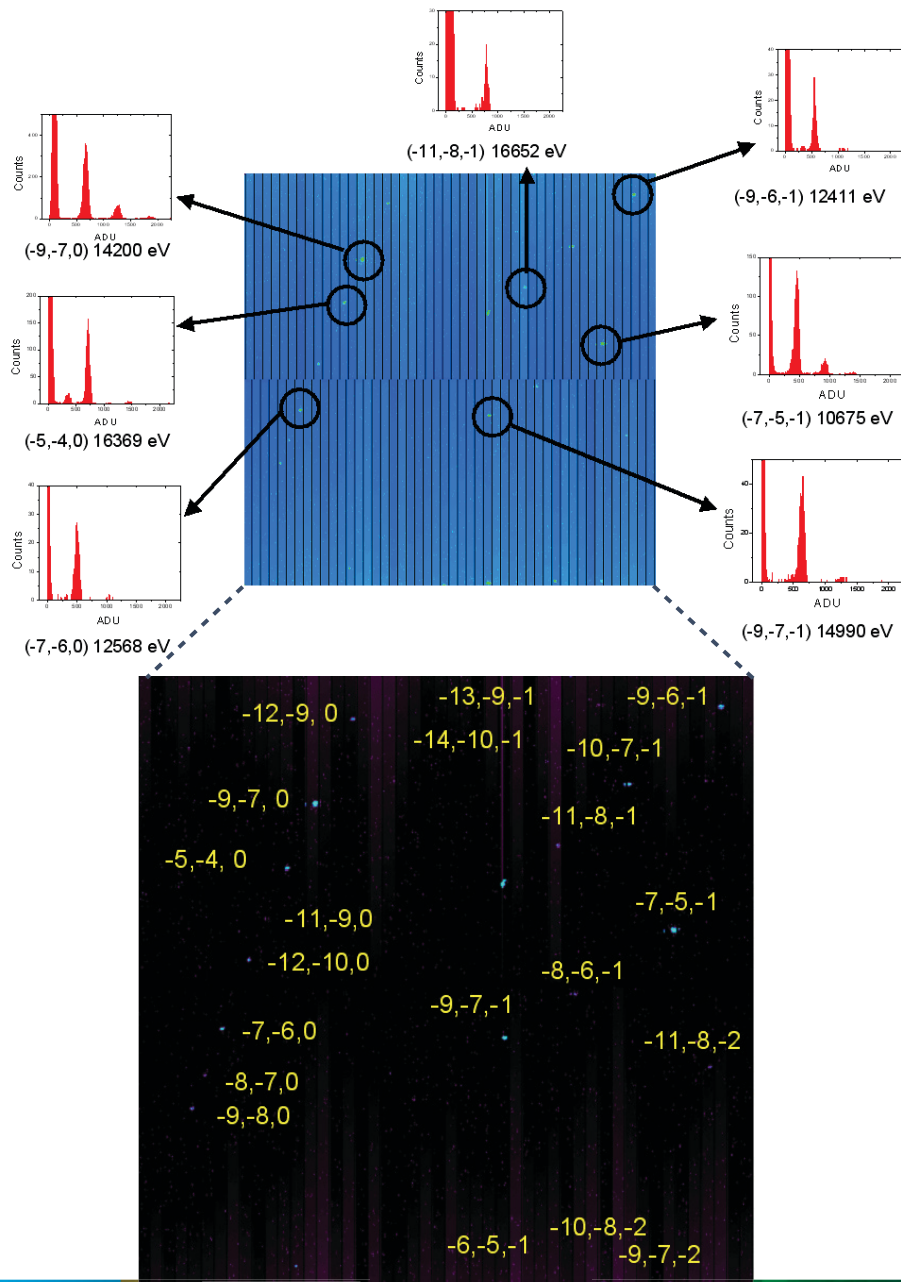


Fatigue cracking of a High-Pressure turbine blade of a Boeing 737 engine (Courtesy: ATSB)



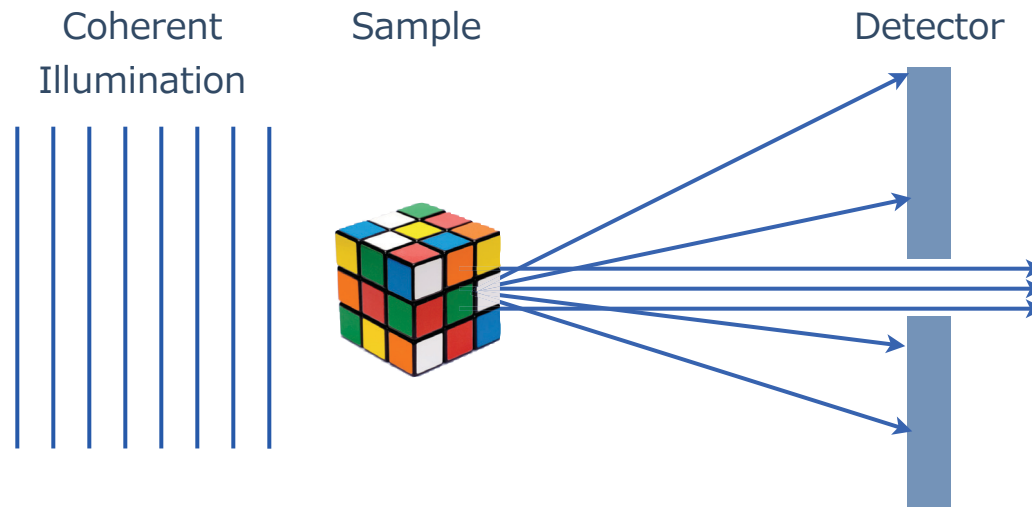
- phase mapping
- grain orientation mapping
- strain mapping
- dislocation density mapping

Developing Fast Energy-Resolved Laue Microdiffraction



- Proof-of-Principle on ALS BL 12.3.2
- CCD is analog → energy resolving
- Acquire data rapidly enough to record \sim individual photons, and reconstruct spectra
- Measure the energy of each reflection
- Alternative to monochromator scan
- Do all N energies at once
- Needs very large solid angle

Coherent (lensless) Imaging



Crystallography for non-crystalline objects

- Dynamic range

- Intensity $I \sim 1/\sin^4(\theta)$

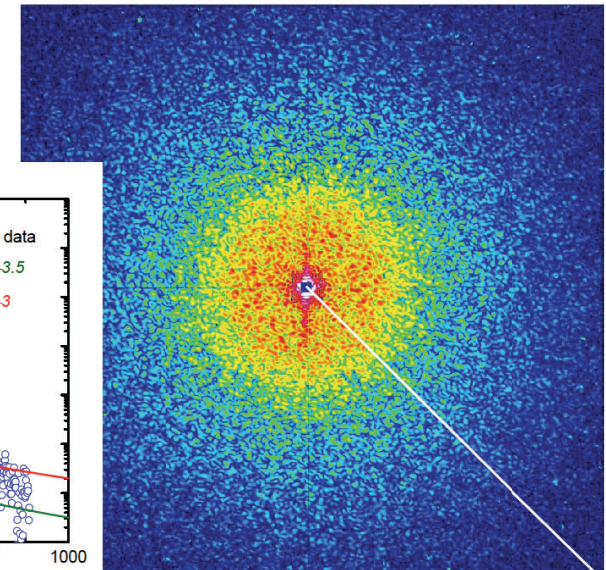
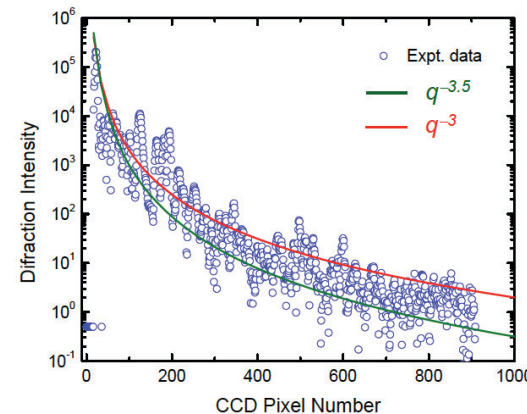
- Noise

- Single photon

- Size

- Resolution $d \sim \lambda/\sin(\theta)$

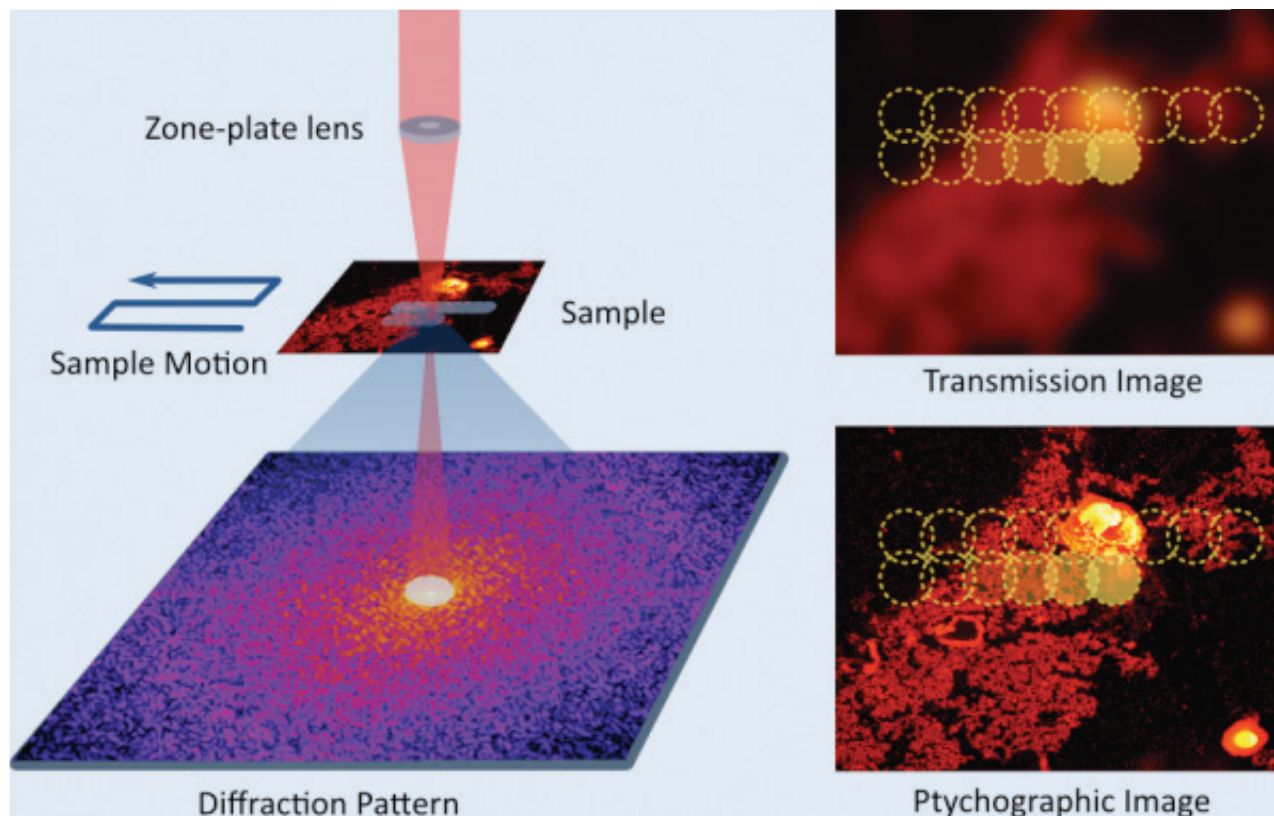
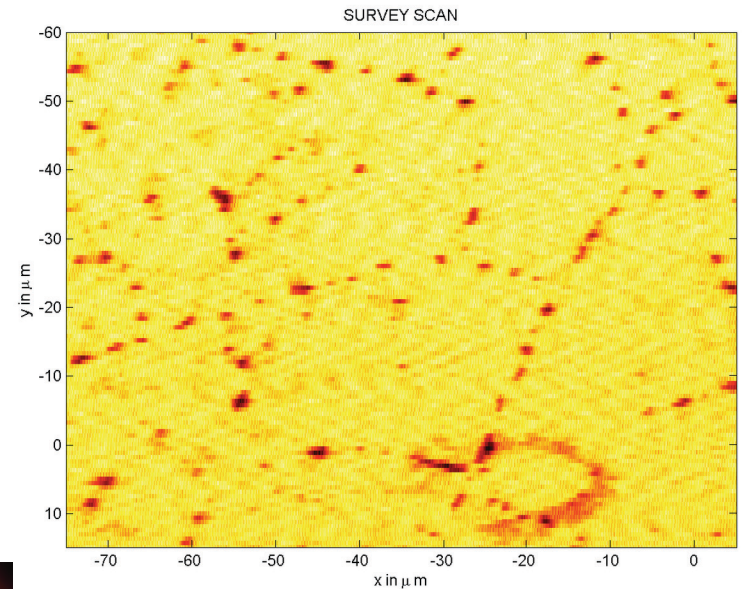
- Small objects \rightarrow large angles / detectors



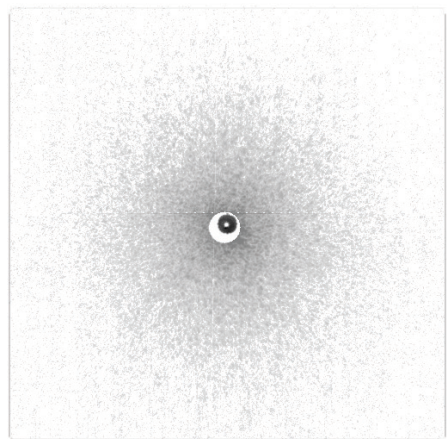
Au nanofoam Shen et al. APS

Ptychography

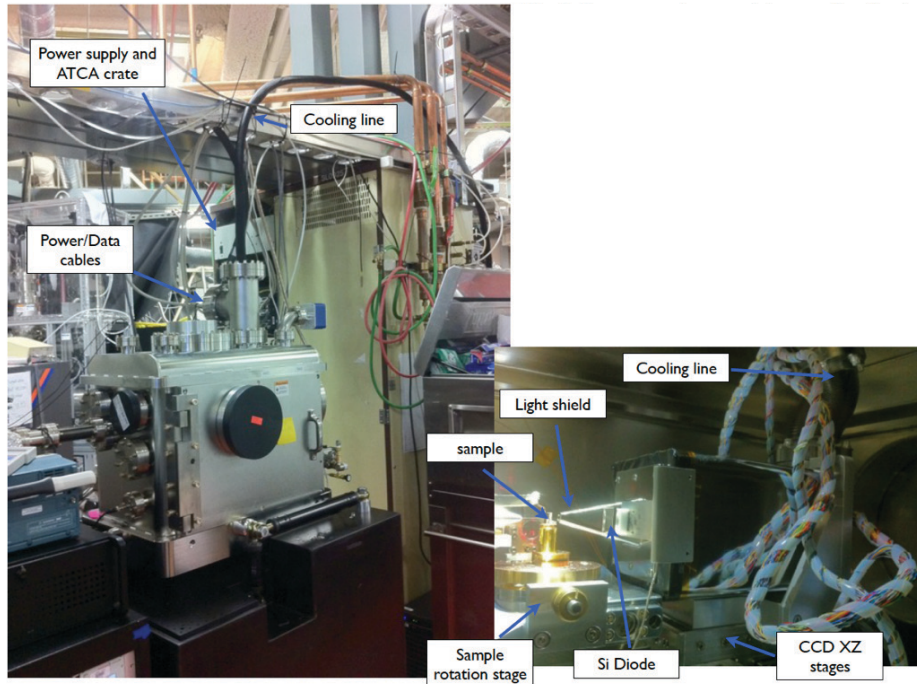
- Scanning microscopy
 - But record diffraction pattern at each point
- Hard X-rays → Pilatus@SLS
- Soft X-rays → FastCCD@ALS



ALS Nanosurveyor

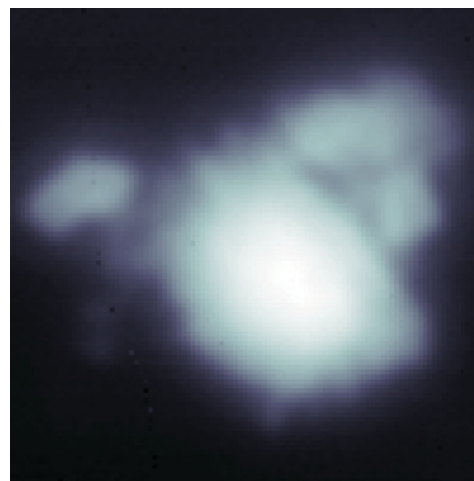


- Concrete - energy and GHG intensive
 - 5% of manmade GHG
- Water + cement \rightarrow $\text{CaO-SiO}_2\text{-H}_2\text{O}$
- Goal is understanding composition and formation of C-S-H

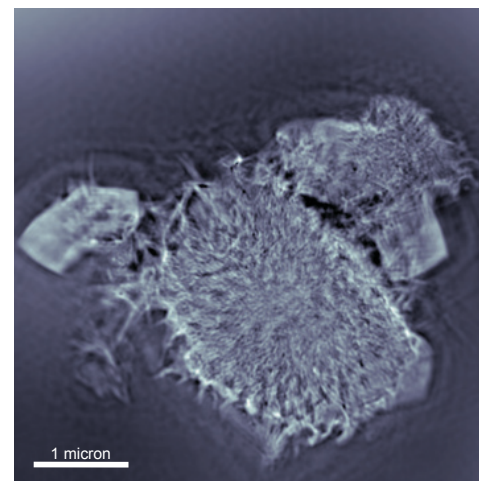


Calcium Silicate Hydrate
Paulo Monteiro's group, UCB

- 50x50 scan points
- 5x5 microns (100 nm step size, 300 nm beam)
- 400 ms exposure per point
- 10 minutes total acquisition time
- single exposures with the beamstop



300 nm STXM
50 nm pixels

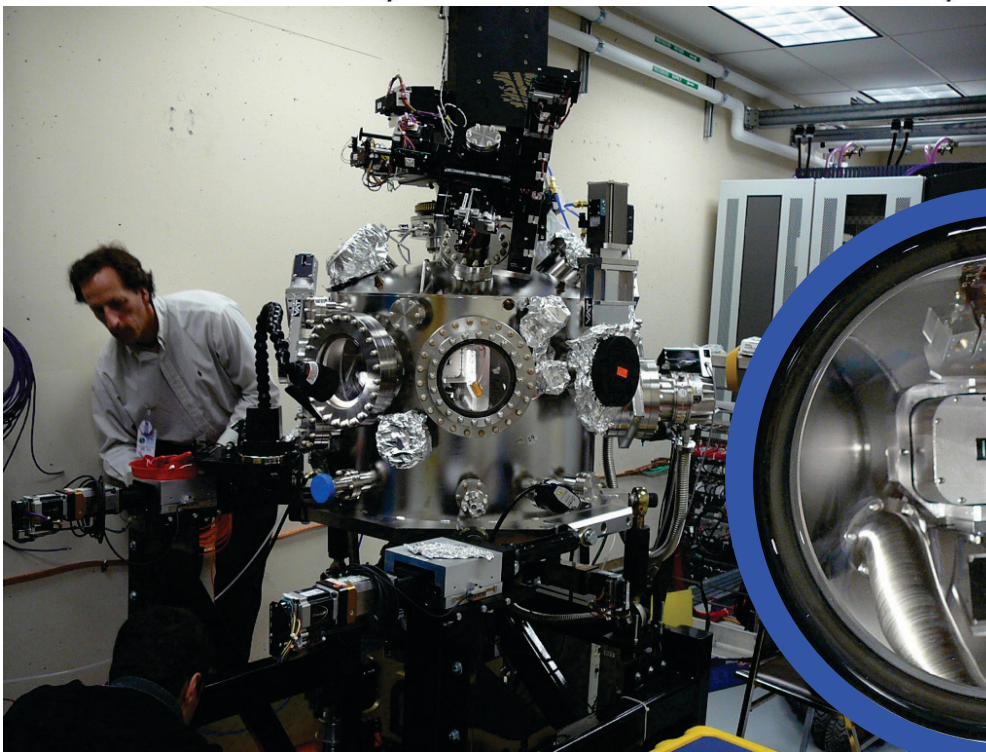
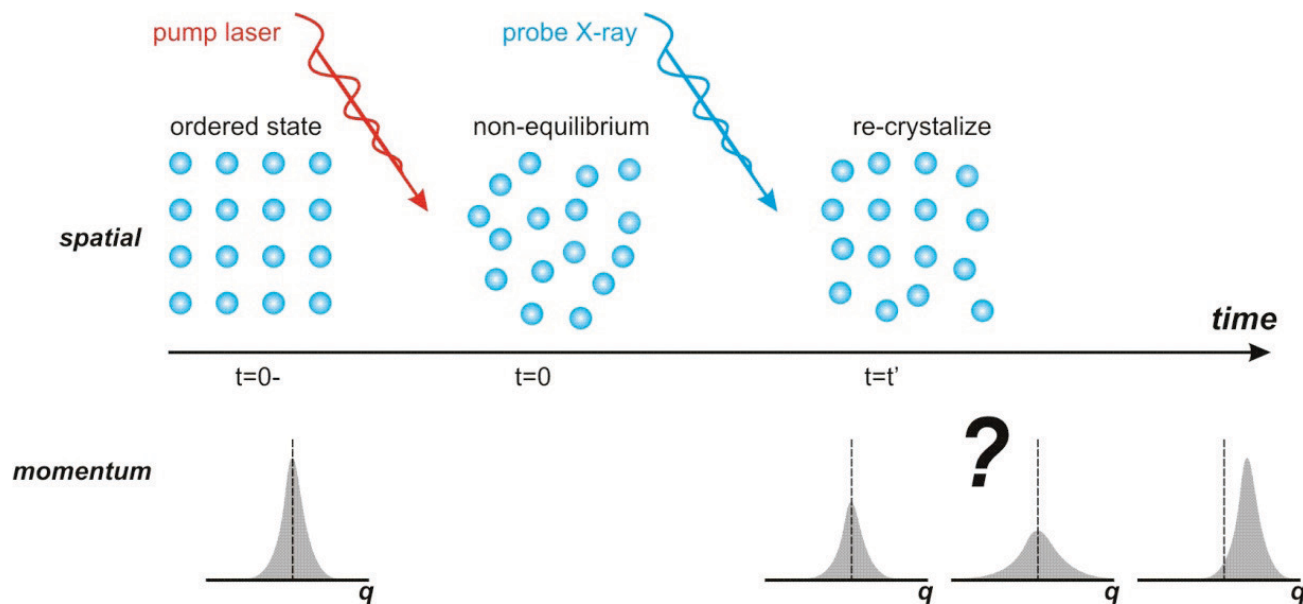
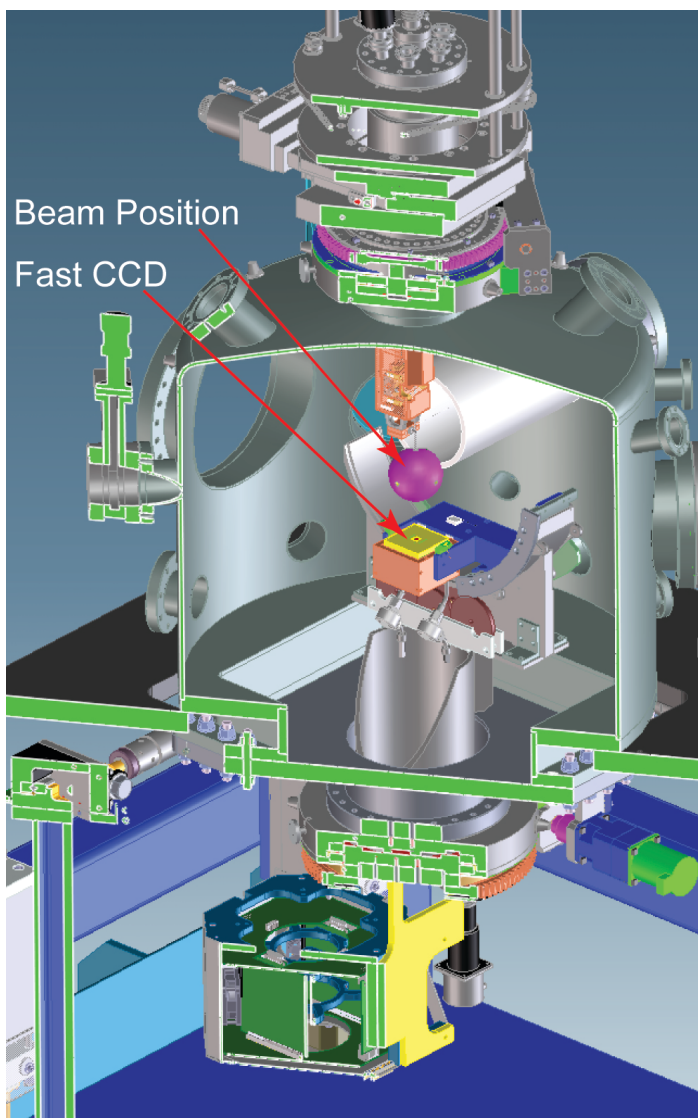


Ptychography
7 nm pixels

Friday, April 26, 13

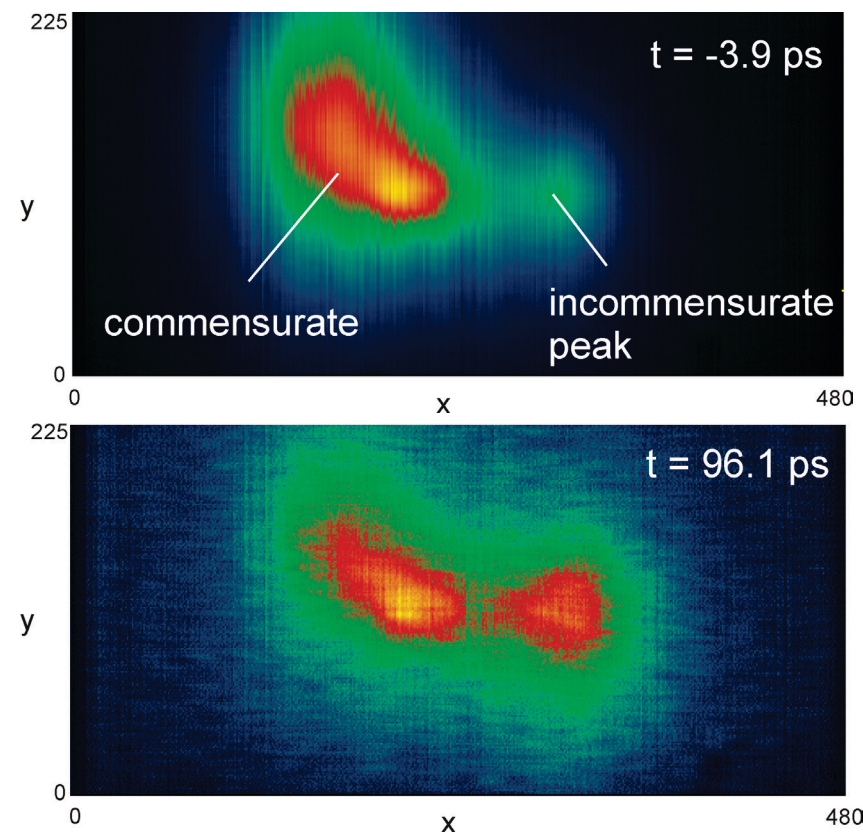
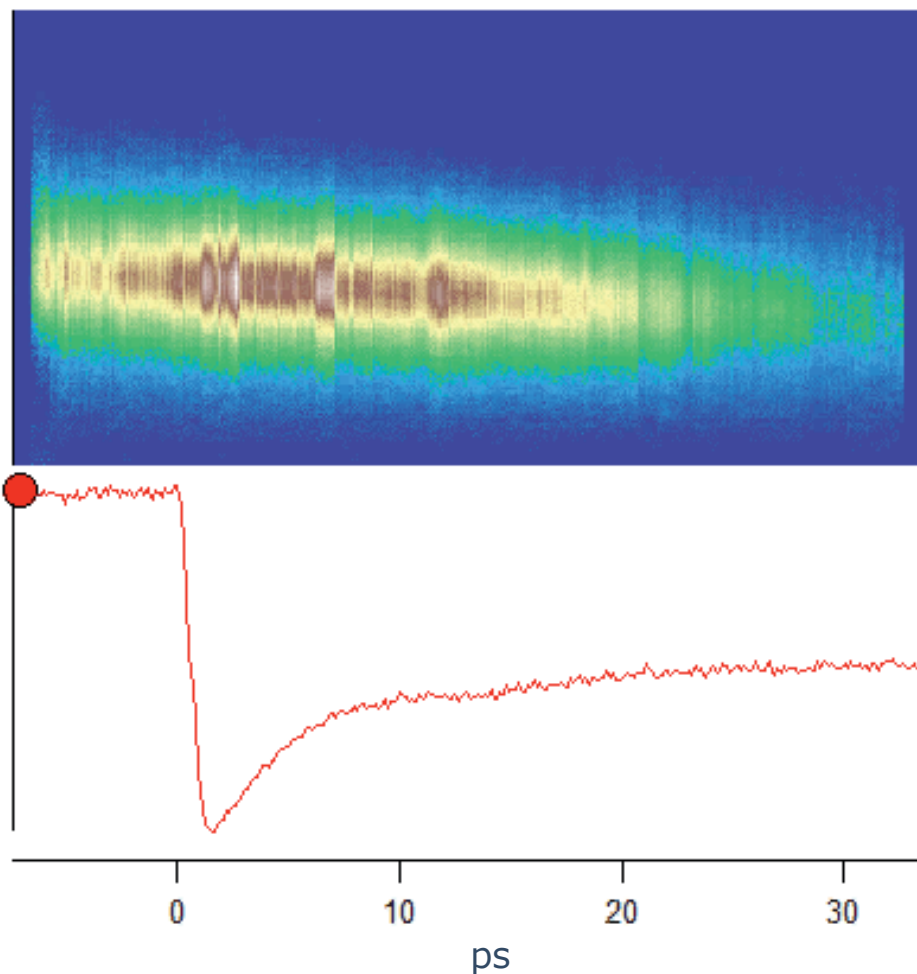
LCLS - RIXS

RSXS Chamber for LCLS Soft X-ray



Spin Ordering (SO) – The Movie

Fast melting and slow recovery of spin ordering around 50K
(shot-by-shot readout to correct time jitter and intensity fluctuation)



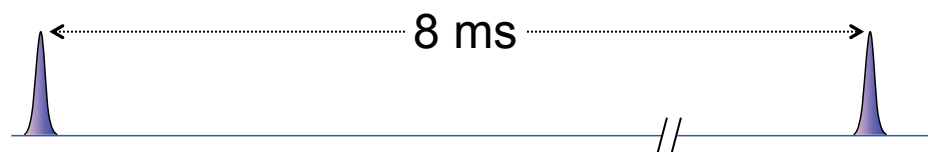
Aug. 2010 - 28 mJ/cm²

FELs



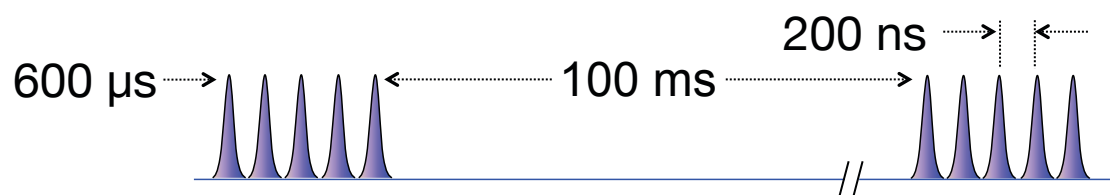
120 Hz

pulsed n.c. HXR



5 MHz
x 0.6%

pulsed s.c. HXR
(FLASH - SXR)

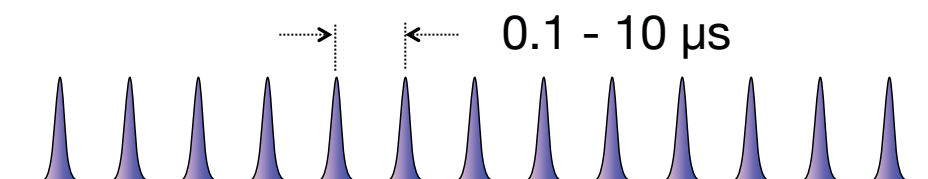


write fast, read slow



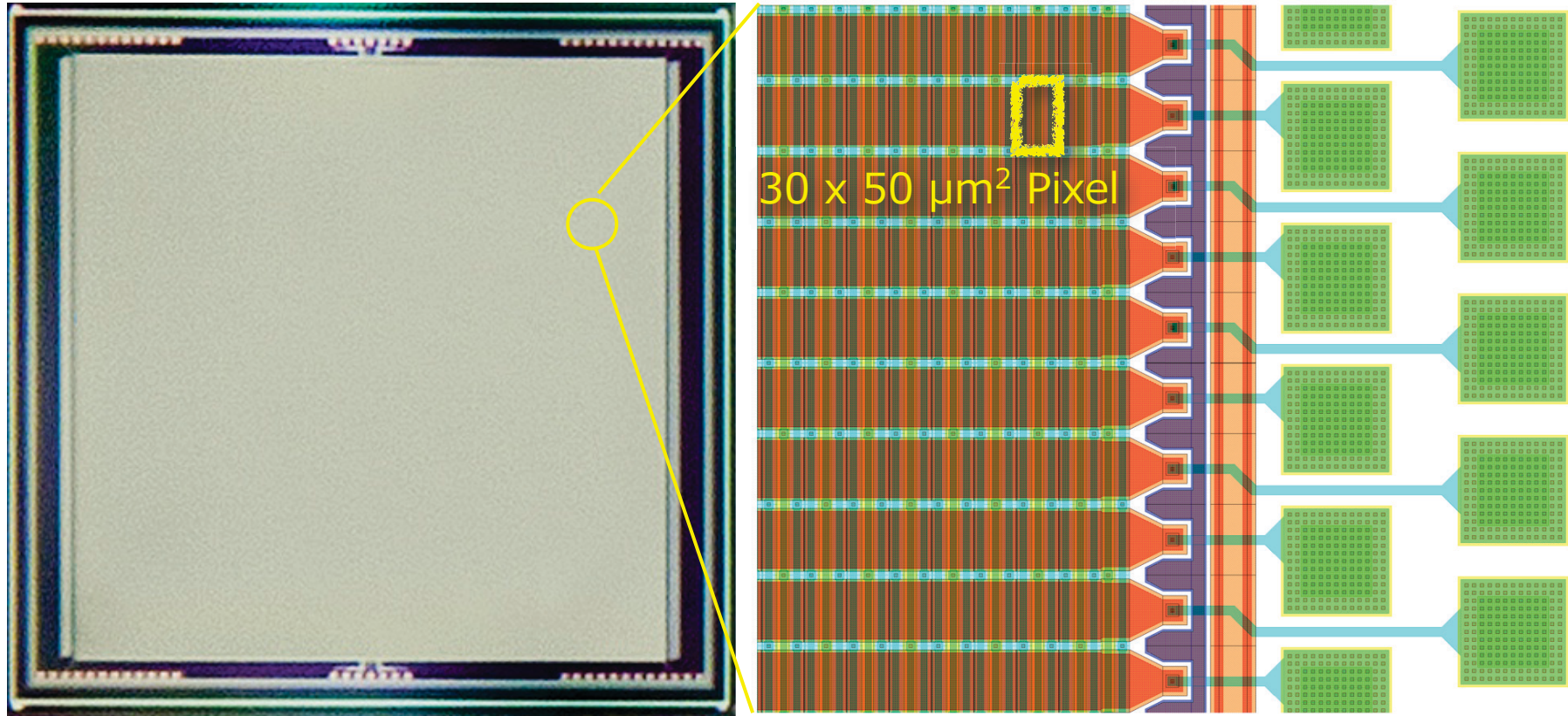
100+ kHz

cw s.c. SXR



continuous data

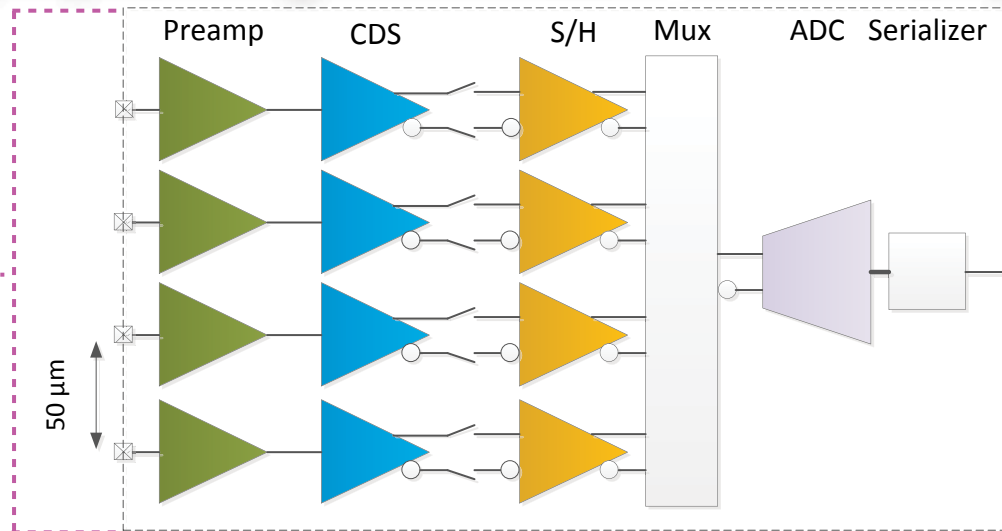
Column-Parallel CCD



- 50 μm pitch for chip-to-chip wire bonding
 - Flip-chip as a next step
- Aim for 10,000 MPix / s
 - Tile 8 x (128 x 1k) to get 100,000 MPix/s

HIPPO High-Speed Image Pre-Processor with Oversampling

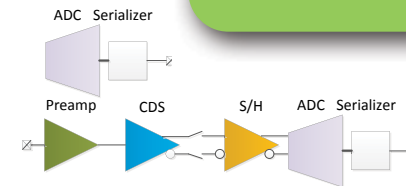
1 4-Channel Cell ...



Meets spec

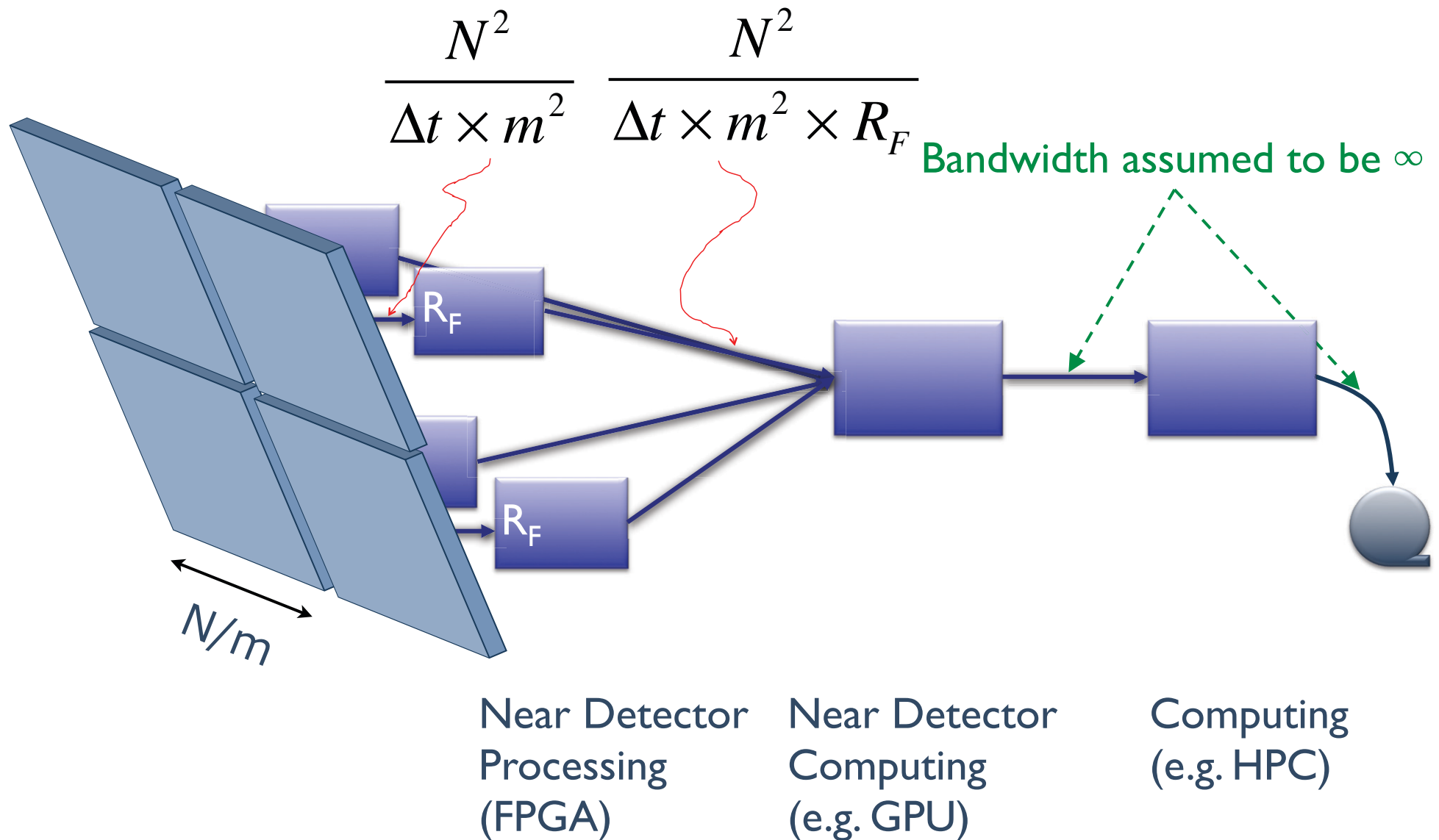
Requirement	Value	Units	Comment
Resolution	12	Bits	
Sampling Rate	80	MS/s	
Full Scale	1	Volts	V_{pp} -differential
Noise (ADC)	200	μV -rms	LSB is 250 μV
Noise (Full)	1.4	LSB	
Linearity	10	Bits	Differential
Circuit Pitch	50	μm	match CCD
Serial Output	480	Mb/s	dual data rate

10 MHz
x 4 (40 MHz)
+ CDS (80 MHz)

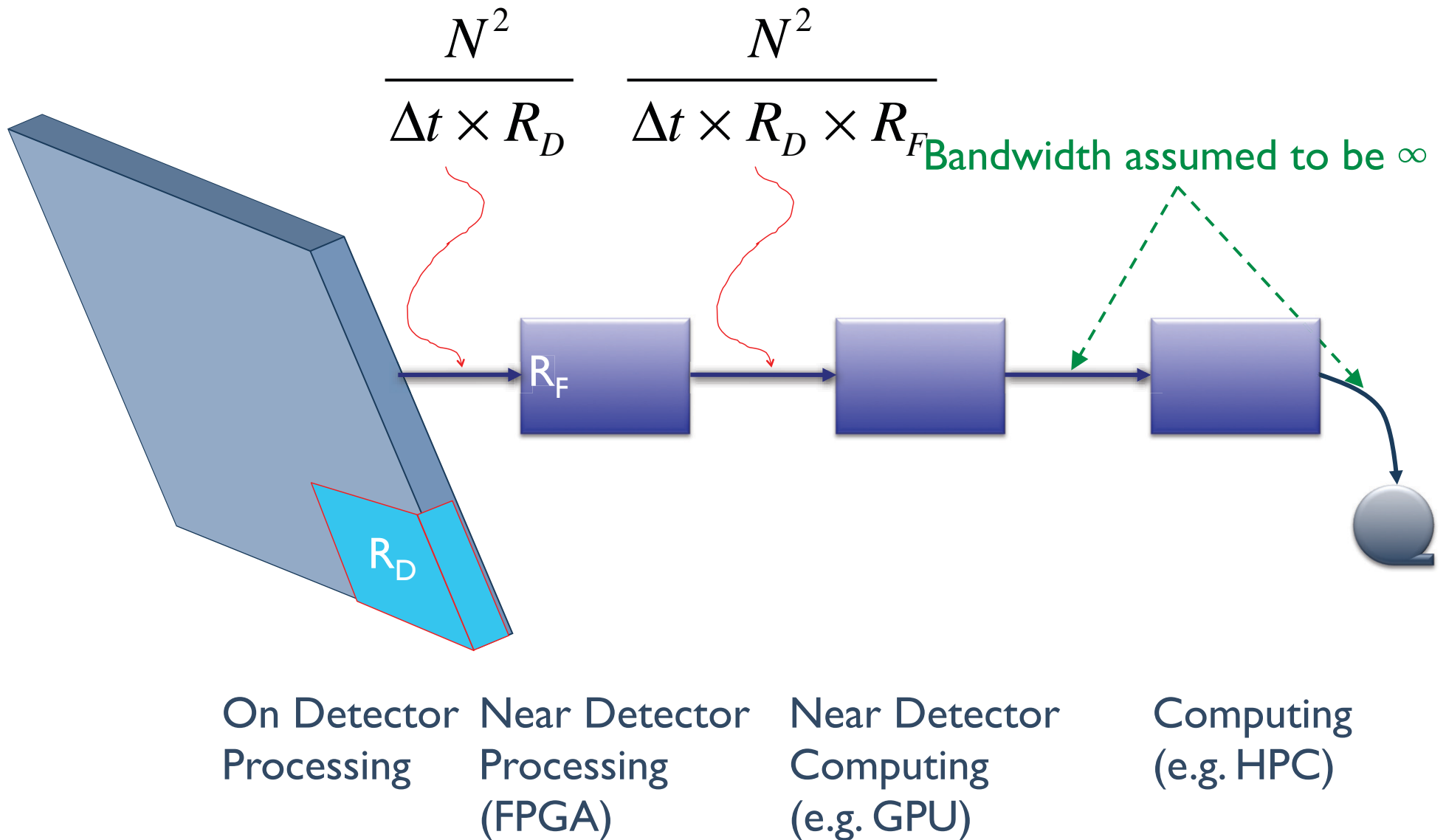


65 nm CMOS - 2011

Data Challenge - Segmentation

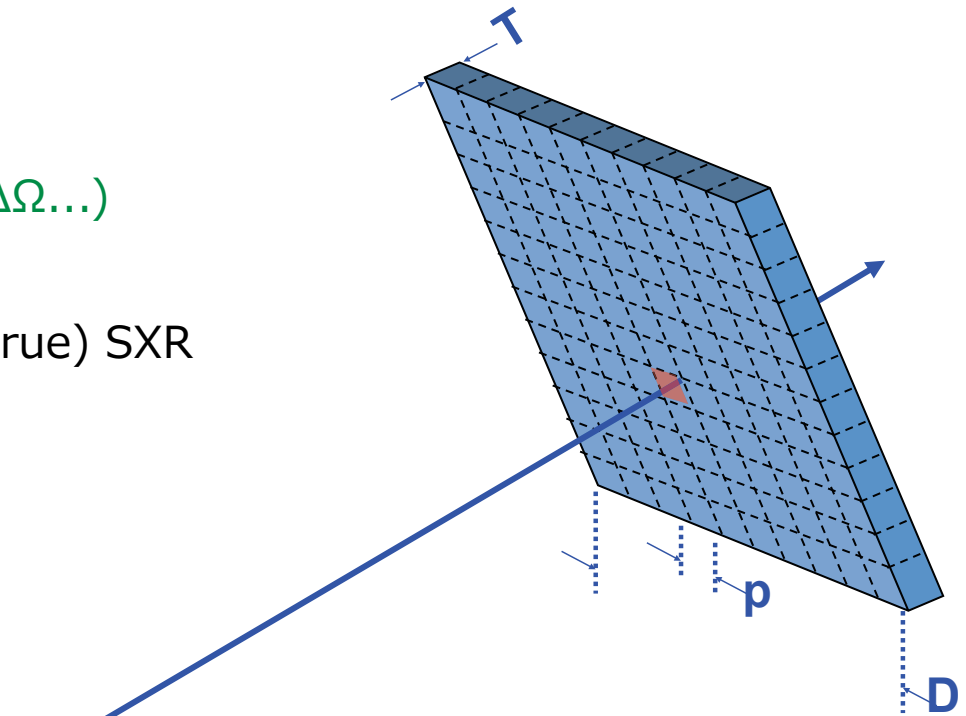
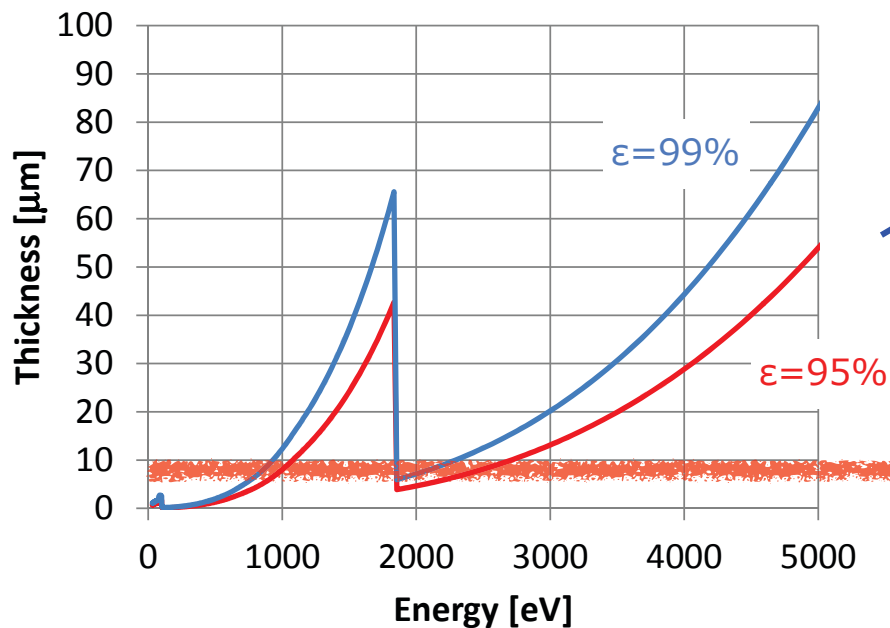


On-chip reduction



Monolithic Soft X-ray Detectors - Good For:

- $N \times N$ pixels
- Pitch p - 5 to 100 μm
- Dimension $D = N \times p$ - 0.1 to 1k ($\Delta\Omega\ldots$)
- Thickness $T(E_Y)_{\text{MAX}}$ - 50 - 300 μm Si
- Radiation hardness not an issue for (true) SXR



Thicker devices for $E > 1$ keV
CMOS possible for $E < 1$ keV

Challenges

Monolithic Si



Efficiency



Size



Resolution



Time



Intensity



Speed

~100%

≪10 μm

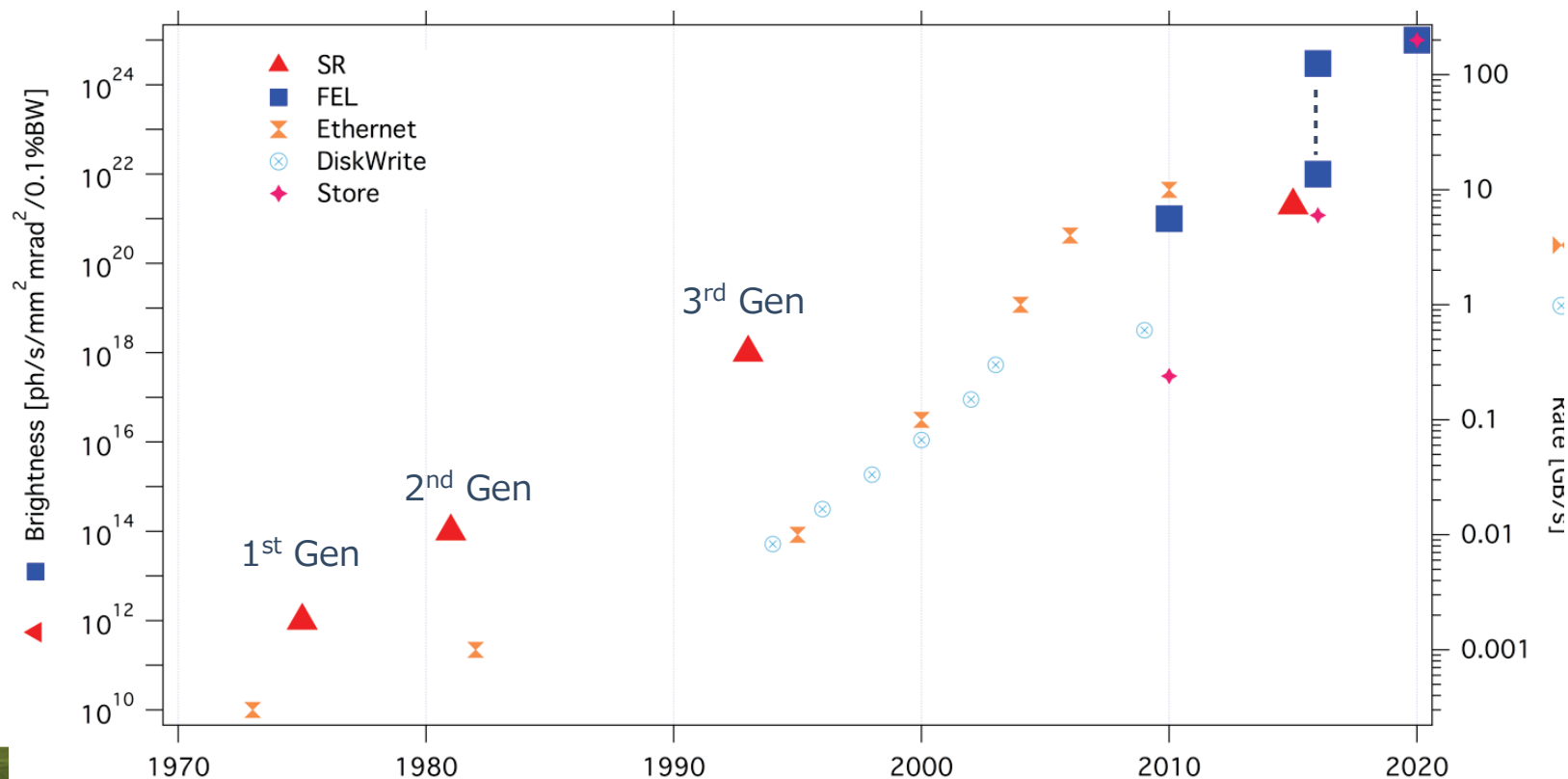
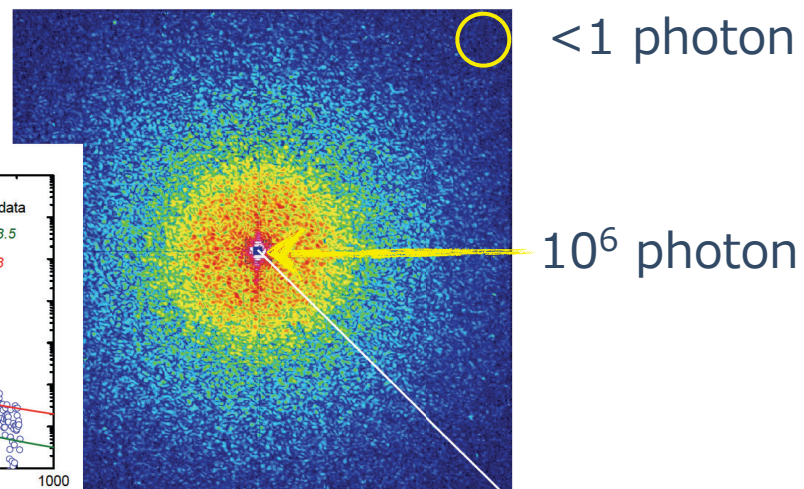
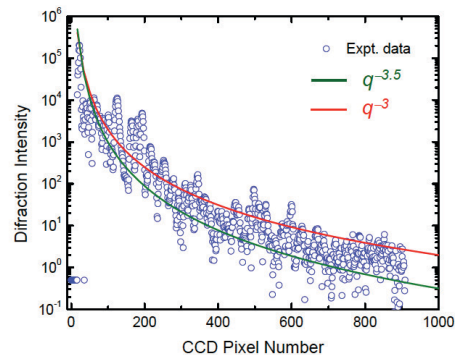
Noise

~10 ns

R&D!

R&D!

Data
challenges
significant!



Thank you!

